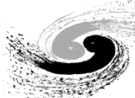


ChiR1.0 - IV 测试

王博新，袁源，徐子骏

2026.08.18



ChiR 第一次流片

	A	B	C	D	E	F	Z	总数
数量	325	325	325	321	321	321	441	2,382

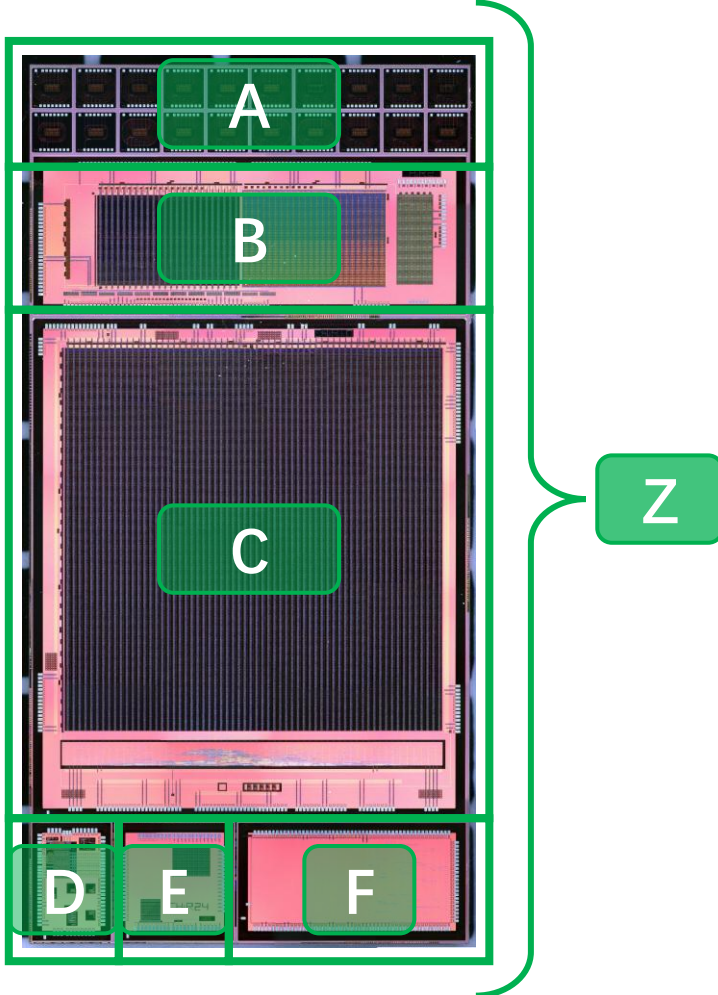
库存记录表

- 按照晶圆、划片、所在的原装硅胶盒号、盒内的第几个芯片，对每一片唯一编号
- 编号规则：

CH1001A103G → CH1001A103G

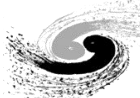
ChiR1.0 流片 AE0408.01晶圆 划片区域A 第1个芯片盒 左上起第3片 良品

索引号	晶圆编号	划片	盒号	序号	是否良品	唯一编号	当前存放位置	入库时间	是否在库	取用时间	取用备注
1	AE0408p01	A	1	1	GOOD	CH1001A101G	物理楼106干燥柜	2026-07-20	1		
2	AE0408p01	A	1	2	GOOD	CH1001A102G	物理楼106干燥柜	2026-07-20	1		
3	AE0408p01	A	1	3	GOOD	CH1001A103G	物理楼106干燥柜（取用盒1）	2026-07-20	0	2026-07-27	测试20个阵列的IV
4	AE0408p01	A	1	4	GOOD	CH1001A104G	物理楼106干燥柜	2026-07-20	1		
5	AE0408p01	A	1	5	GOOD	CH1001A105G	物理楼106干燥柜	2026-07-20	1		
6	AE0408p01	A	1	6	GOOD	CH1001A106G	物理楼106干燥柜	2026-07-20	1		
7	AE0408p01	A	1	7	GOOD	CH1001A107G	物理楼106干燥柜	2026-07-20	1		
8	AE0408p01	A	1	8	GOOD	CH1001A108G	物理楼106干燥柜	2026-07-20	1		
9	ΔF0408p01	Δ	1	9	GOOD	CH1001A109G	物理楼106干燥柜	2026-07-20	1		



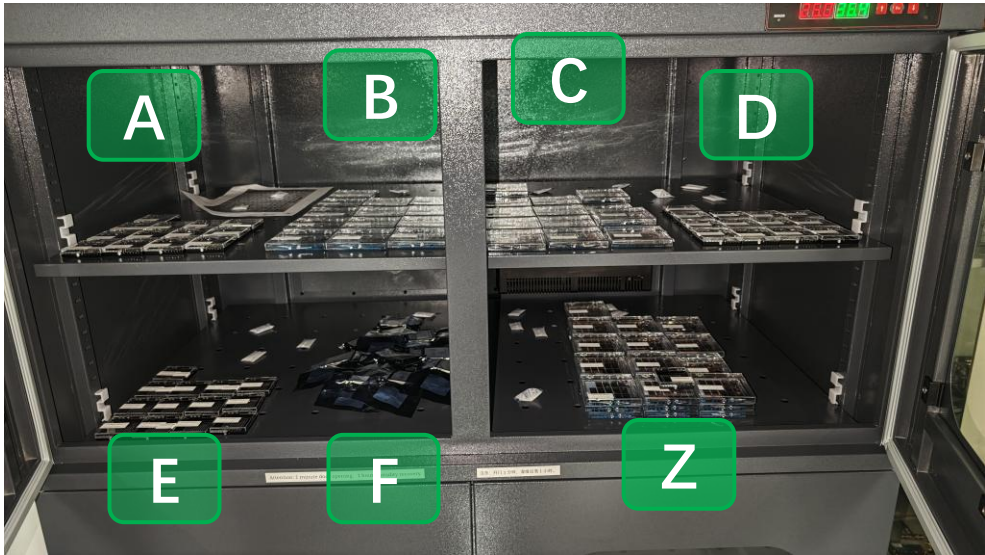
- 已上传 IHEP Box，如有取用随时更新

准备：ChiR1.0 芯片库存列表



- 目前已全部收纳到三号厅 007 实验室的电子防潮柜内
- 已寄出（已出库）的情况：

院所	日期	芯片列表	数量	签收人
西北工业大学	2026.07.20	CH10[04,05]F1[01-25]G	50，阵列F	魏晓敏
浙江大学	2026.08.11	CH1001A1[01,02]G CH10[02-13]A1[02,03]G	26，阵列A	朱宏博
大连民族大学	2026.08.14	CH10[01-13]D1[01,02]G CH10[02,06]D103G	28，阵列D	施展

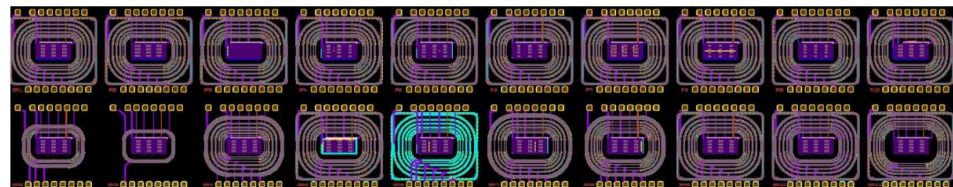


ChiR1.0 子阵列 A

- 以 GR1 为基准, P2~P10 为不同的像素设计, GR2~GR11为不同的保护环设计

IV 测试

- IV 测试的目的是获取击穿电压。
- HV 接入 P 衬底, NR 接入 N-well ring, 测量这两个 pad 的IV 即可。
- 其他 pad 悬空**、双同轴电缆、2470源表进行 IV 扫描

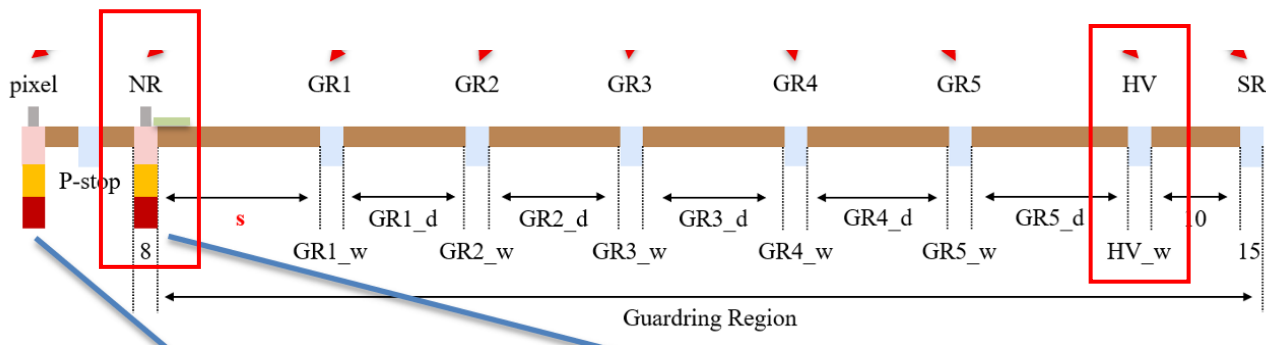
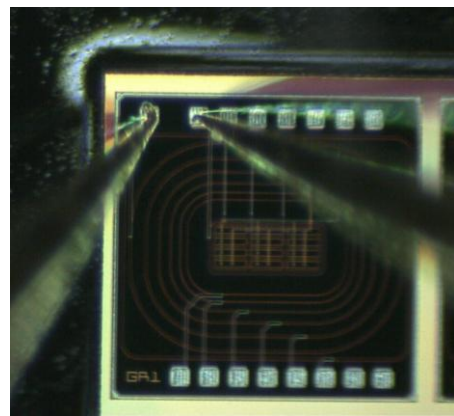
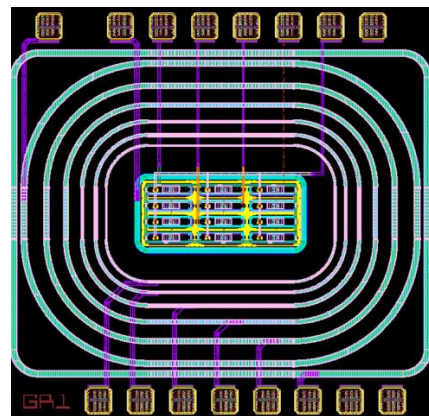


版图总览

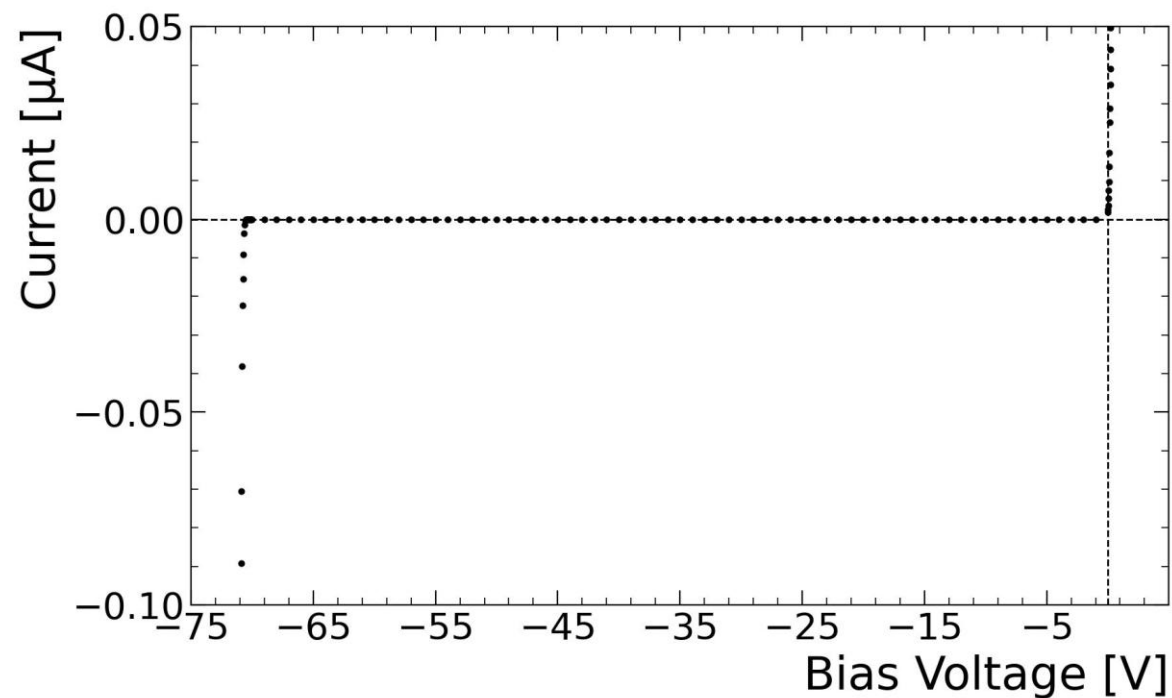
GR1	P2	P3	P4	P5	P6	P7	P8	P9	P10
GR2	GR3	GR4	GR5	GR6	GR7	GR8	GR9	GR10	GR11

分布示意图

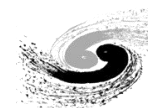
HV NR



- 验证即将使用的源表+探针台是否可复现此前 -70V 击穿的 COFFEE3 IV 图像，以确认仪器和程序工作正常



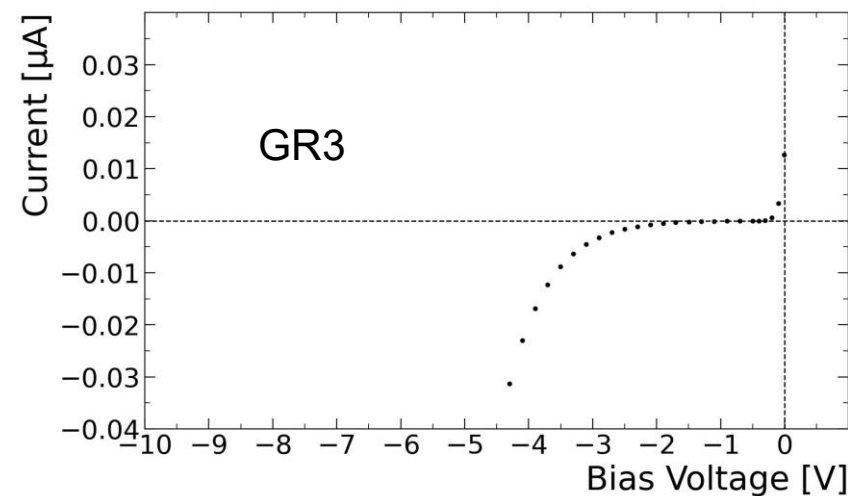
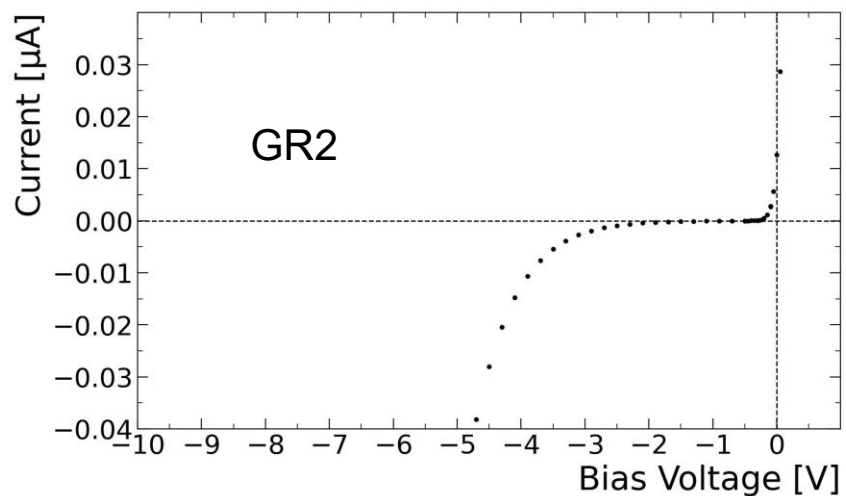
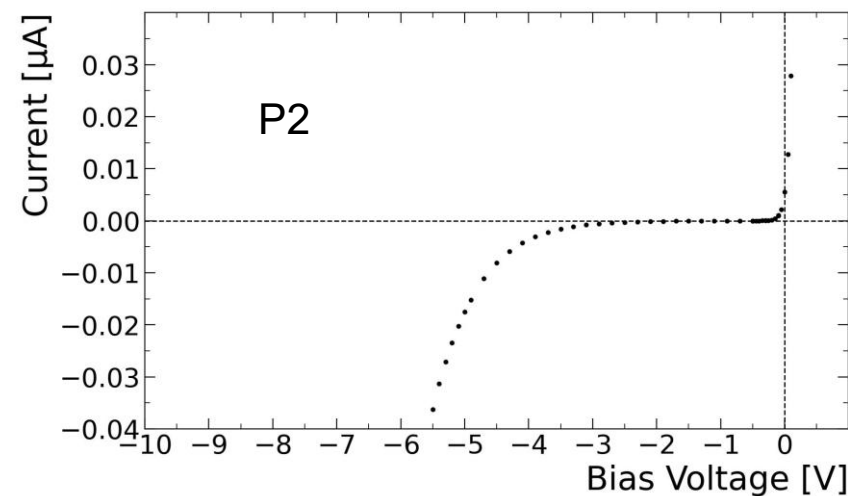
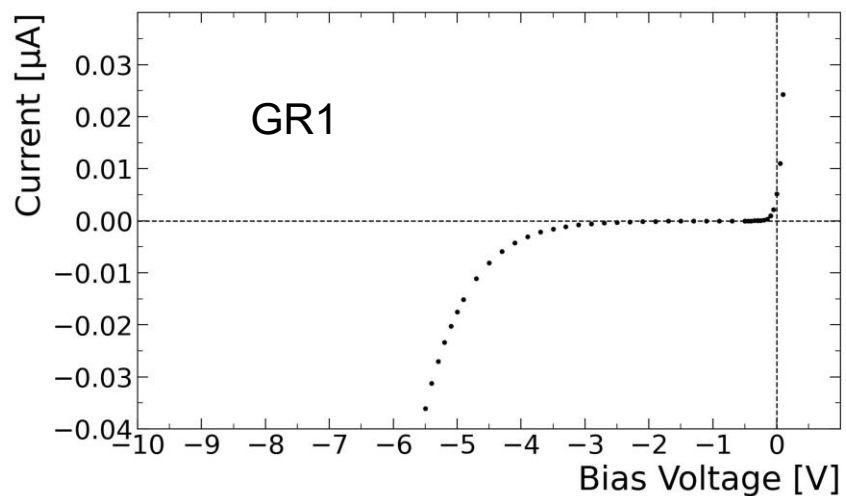
- 仪器和程序都成功复现了 COFFEE3 的 IV 特性，可靠性得以验证



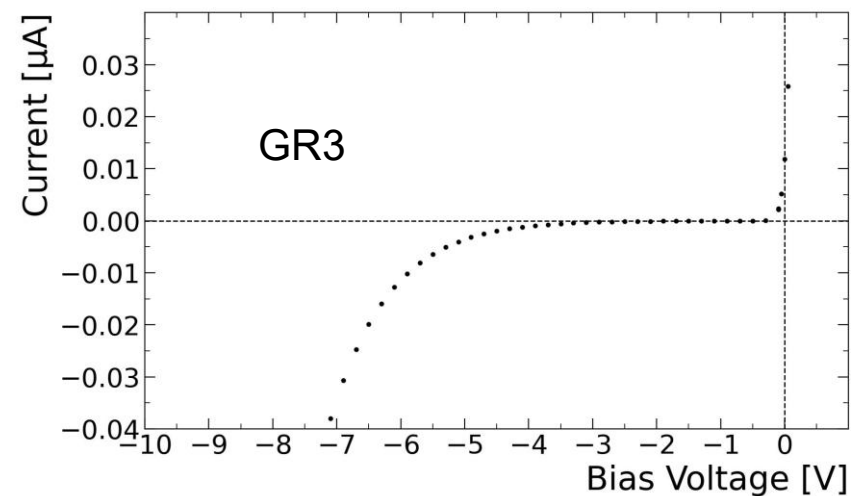
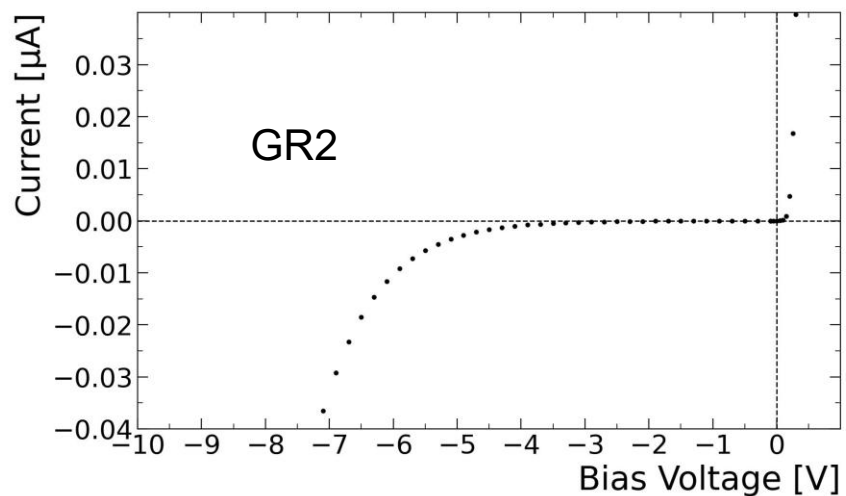
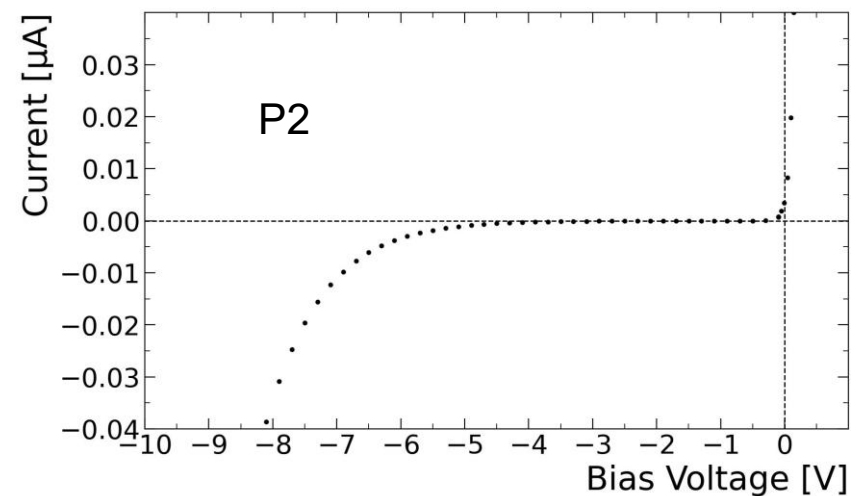
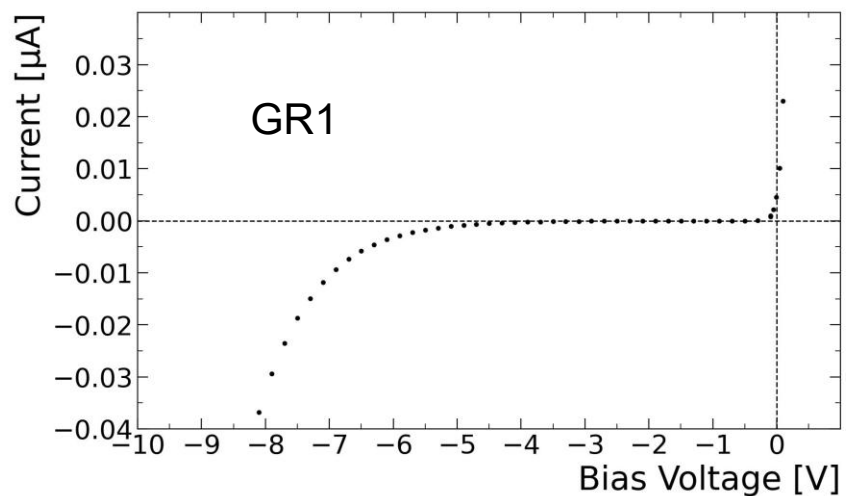
□ 已测试:

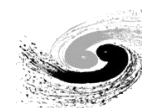
- CH1001A103G -- GR1, GR2, GR3, P2, P3
- CH1002A101G -- GR1, GR2, GR3, ..., GR11, P2, P3, ..., P10
- CH1003A101G -- GR1, GR2, GR3, P2
- CH1004A101G -- GR1, GR2, GR3, P2
- CH1005A101G -- GR1, GR2, GR3, P2
- CH1006A101G -- GR1, GR2, GR3, P2
- CH1007A101G -- GR1, GR2, GR3, P2
- CH1008A101G -- GR1, GR2, GR3, P2, P3
- CH1009A101G -- GR1, GR2, GR3, P2
- CH1010A101G -- GR1, GR2, GR3, P2
- CH1011A101G -- GR1, GR2, GR3, P2
- CH1012A101G -- GR1, GR2, GR3, P2, P3
- CH1013A101G -- GR1, GR2, GR3, P2

□ CH1001A103G

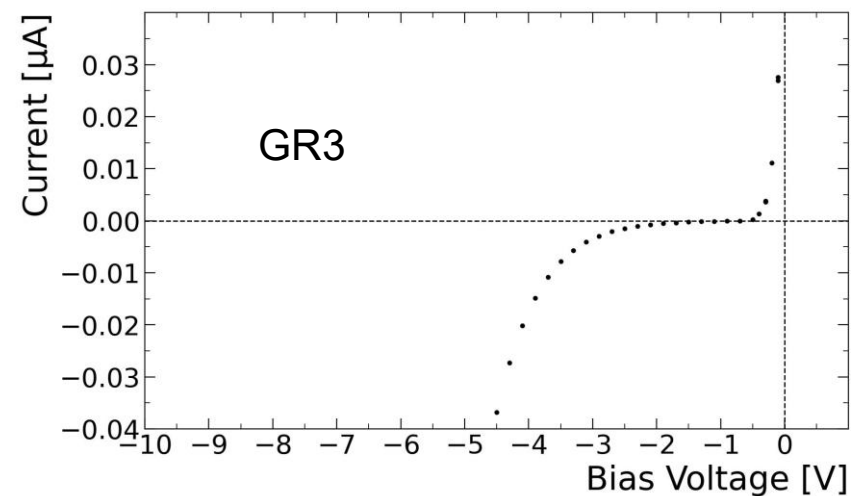
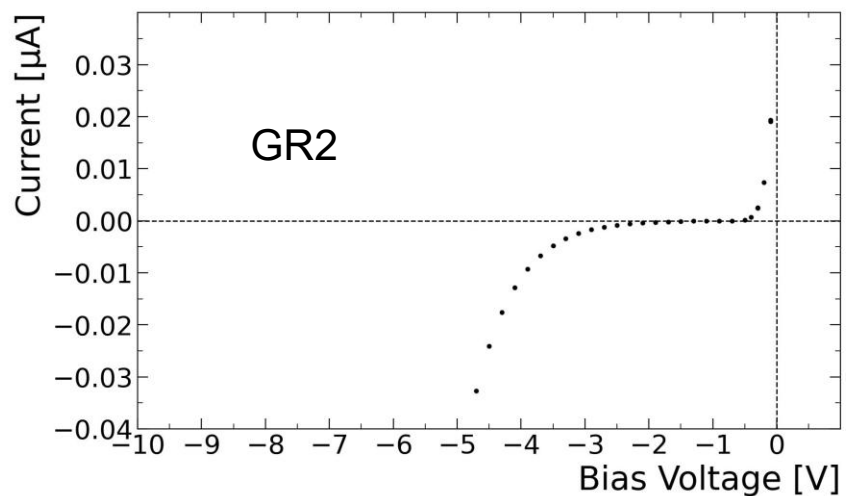
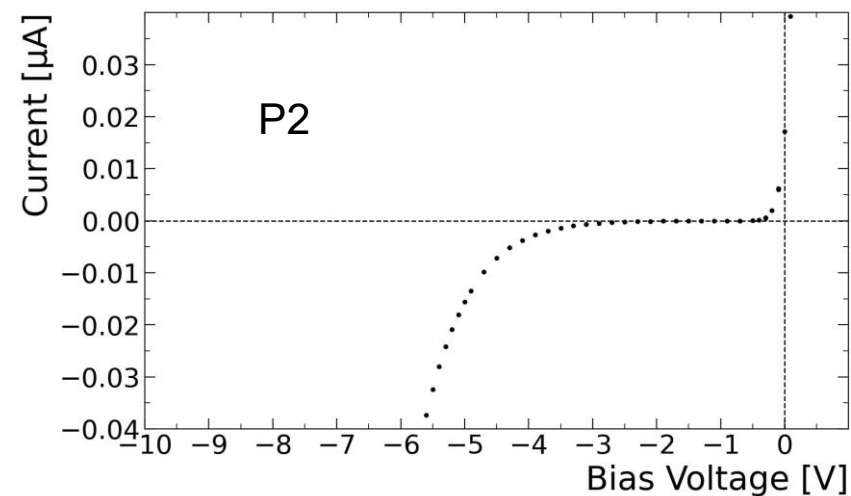
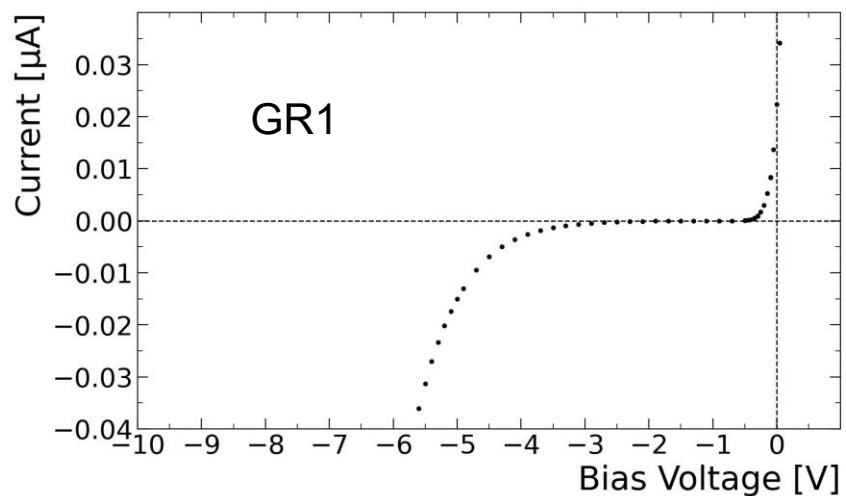


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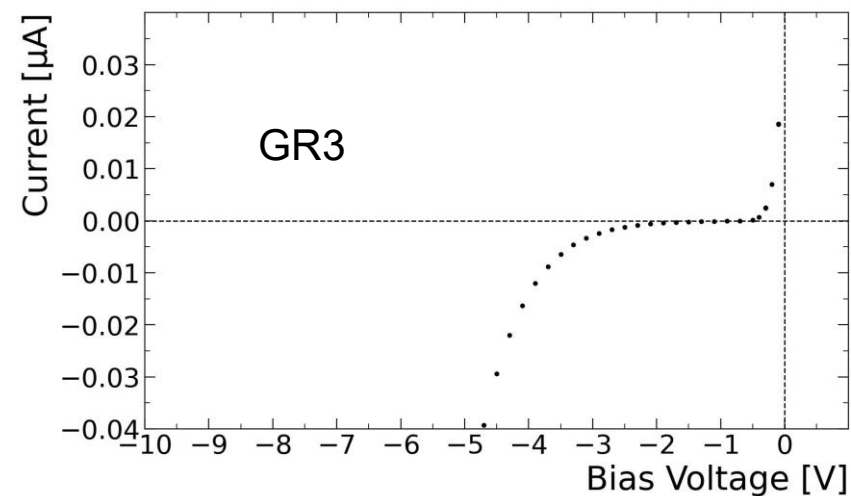
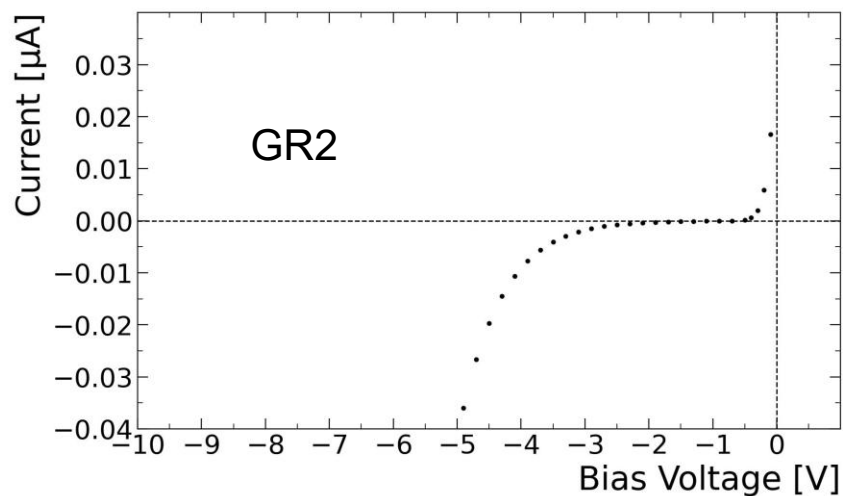
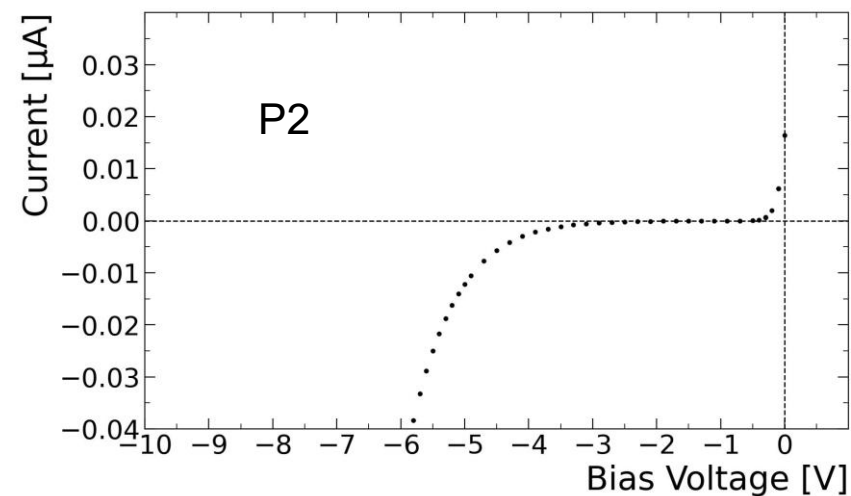
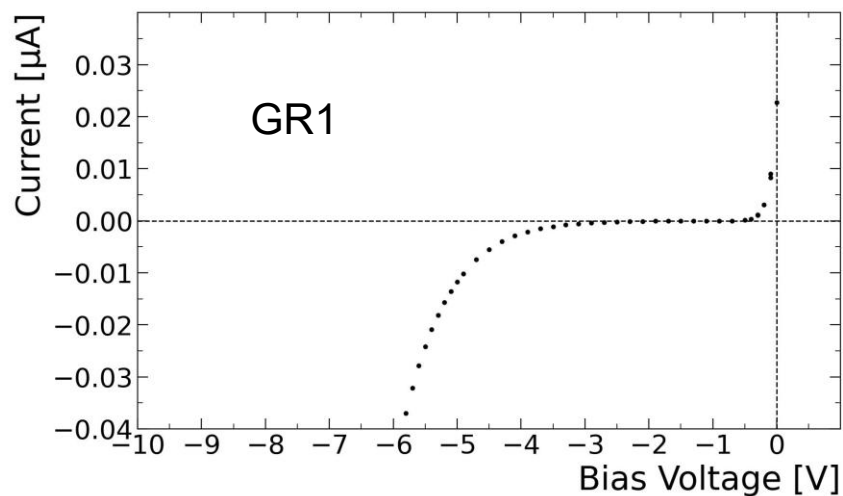




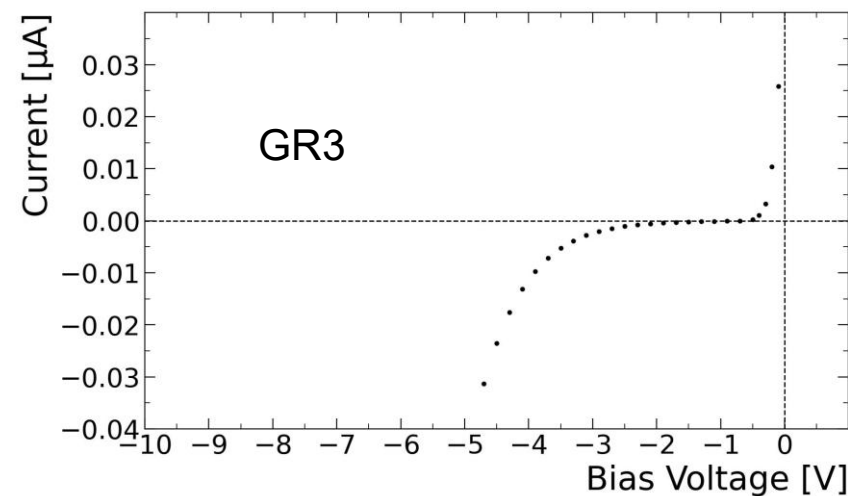
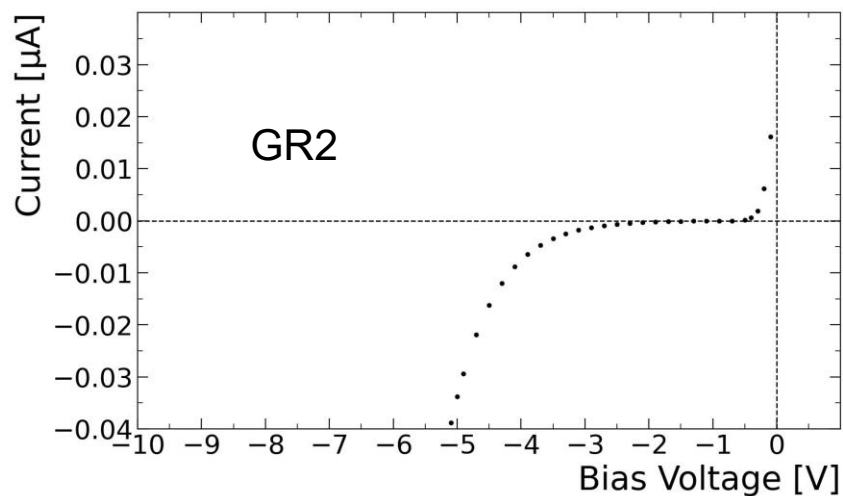
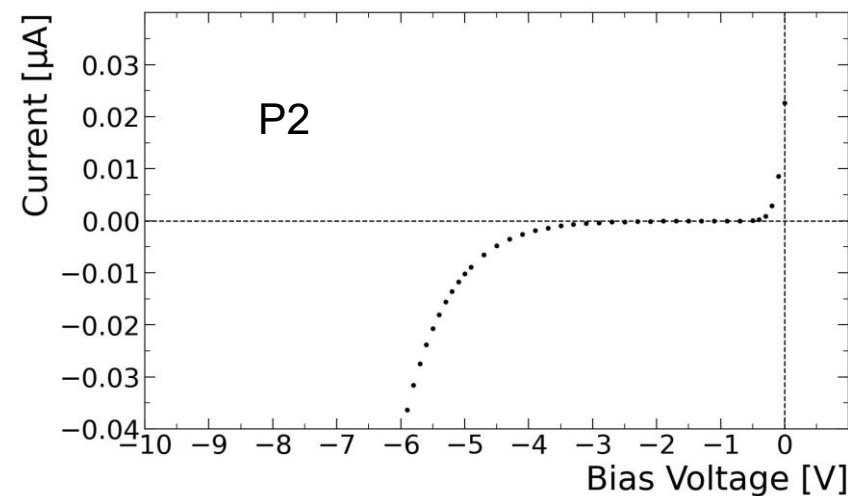
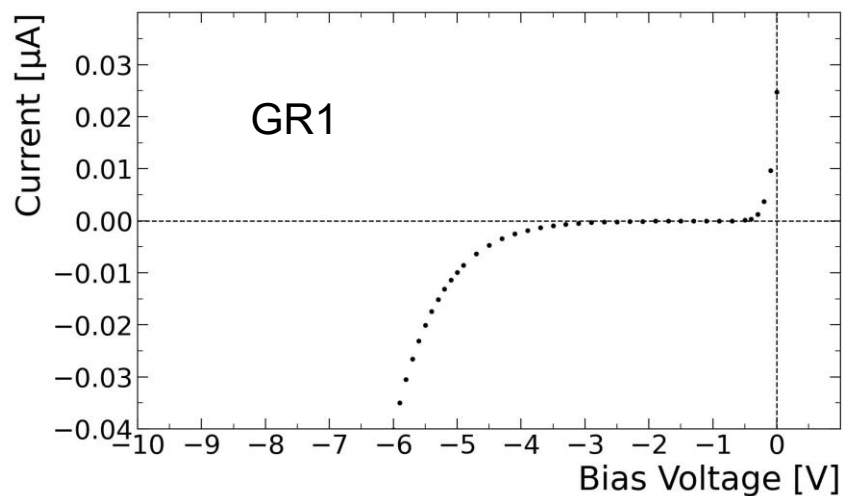
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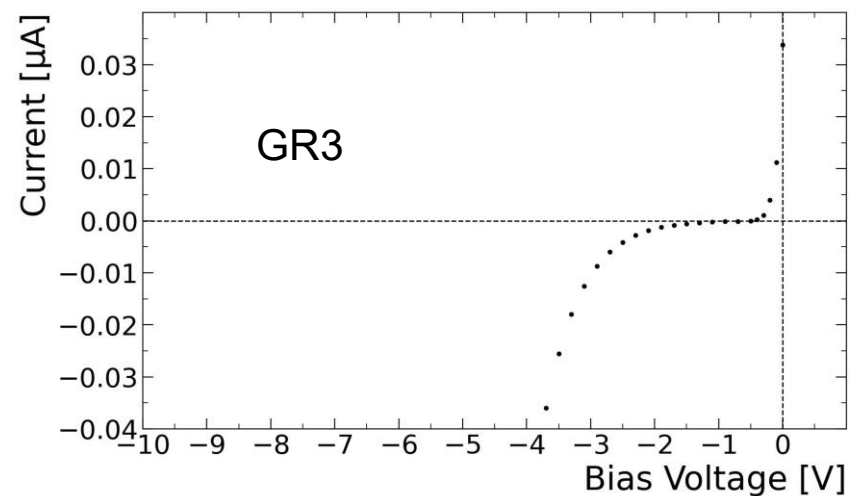
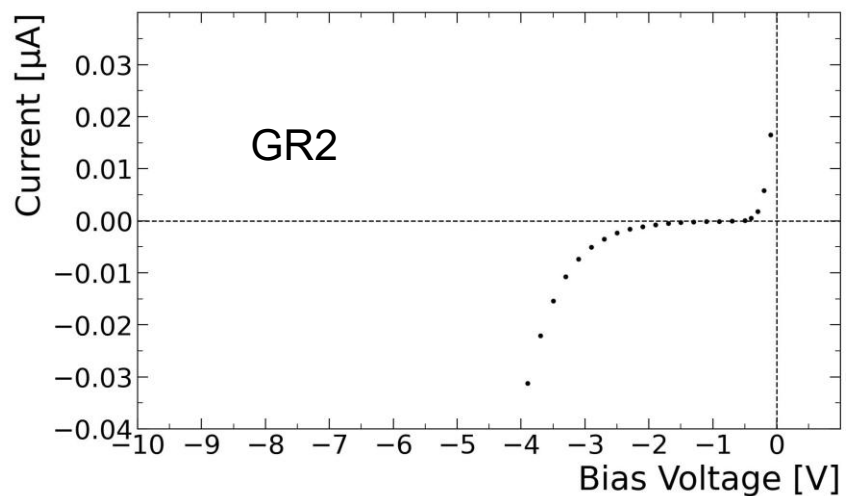
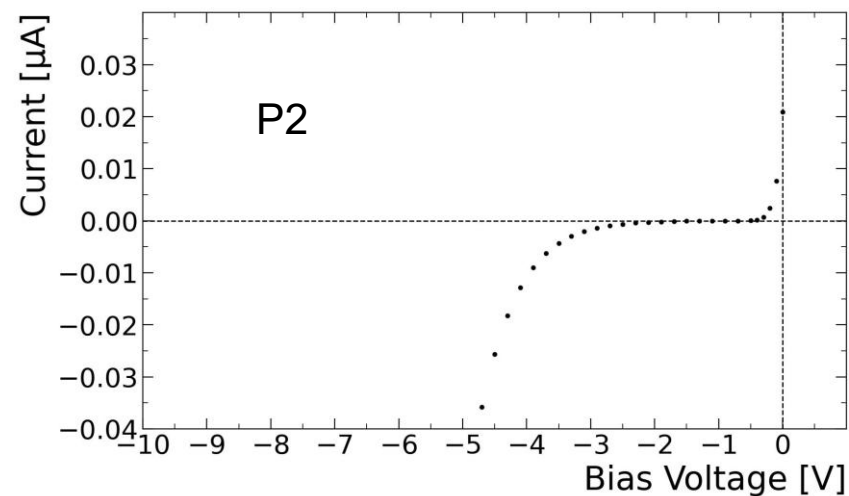
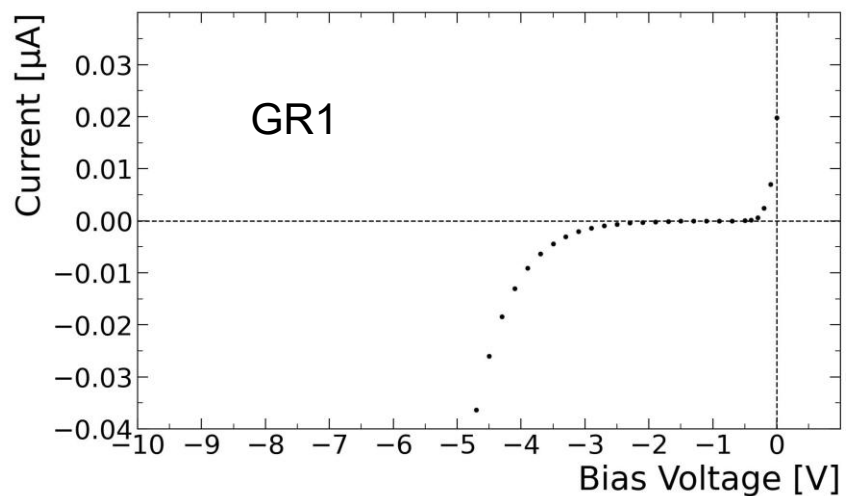
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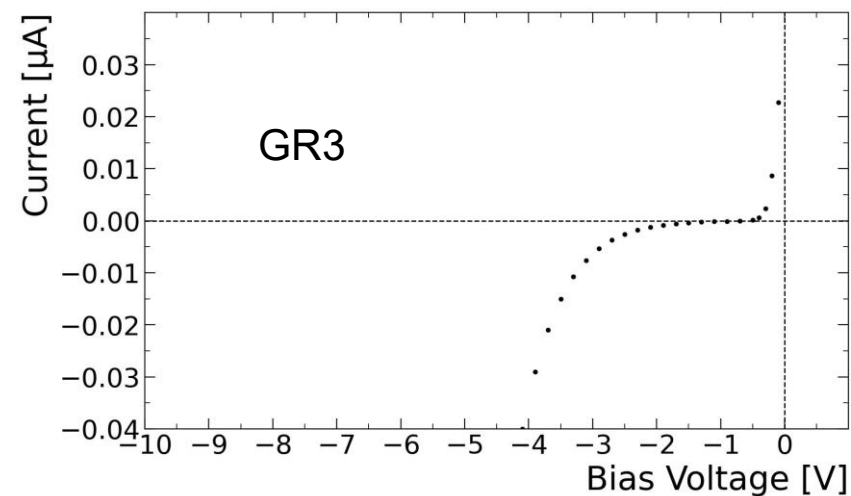
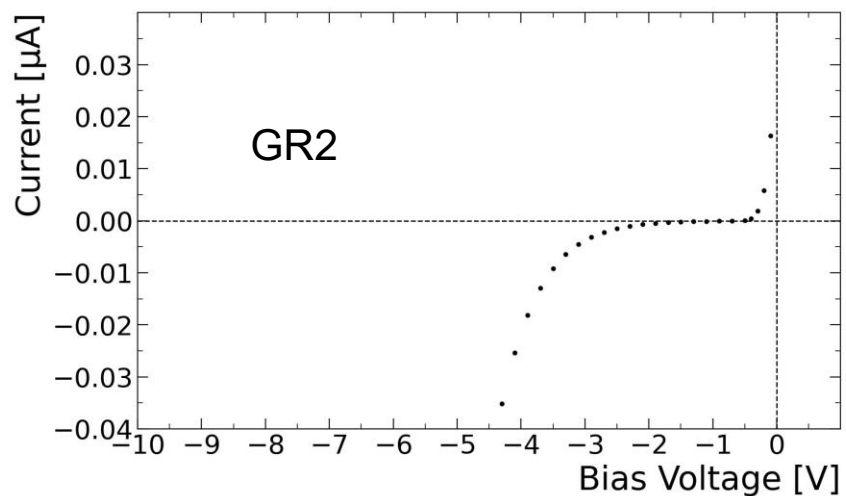
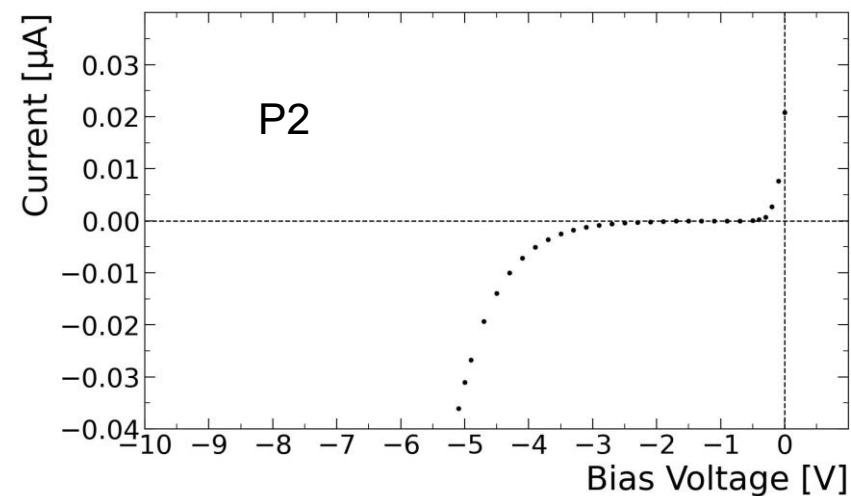
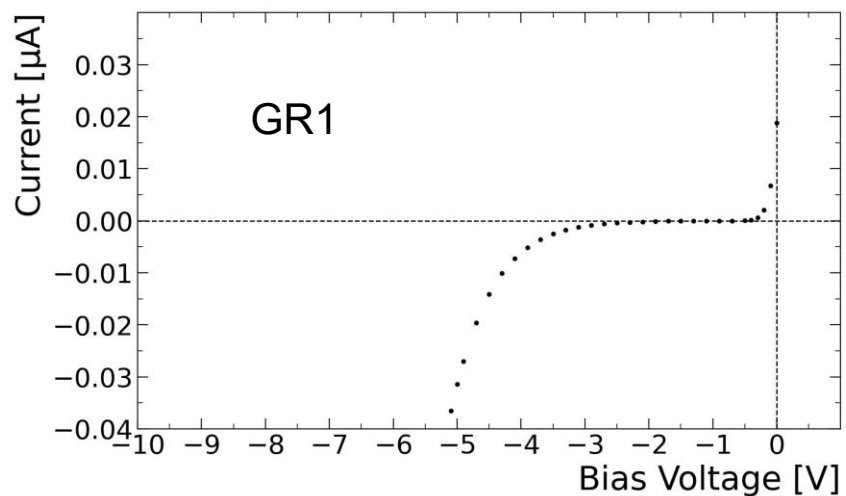
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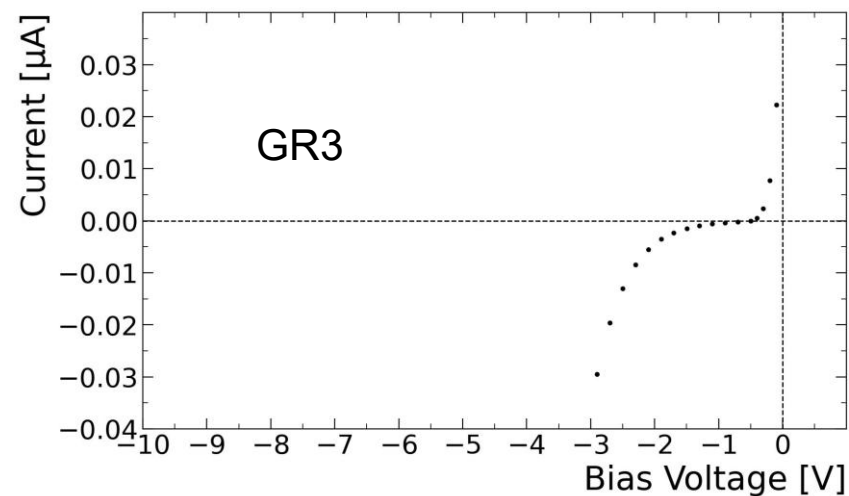
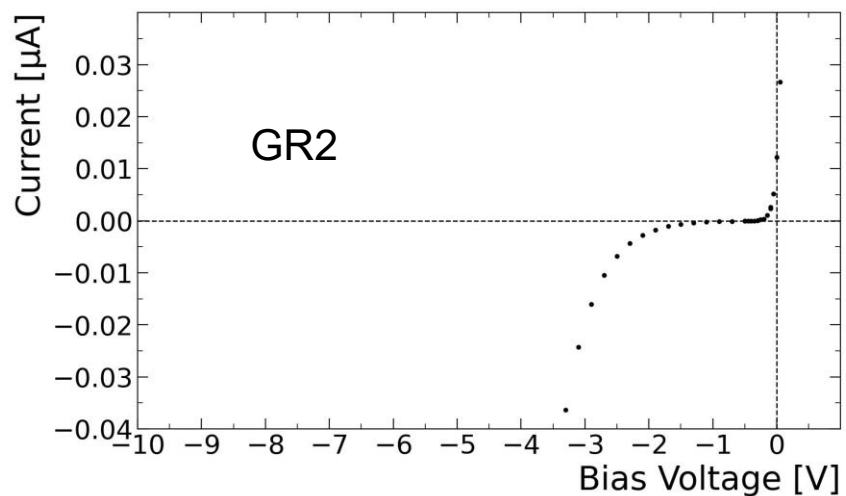
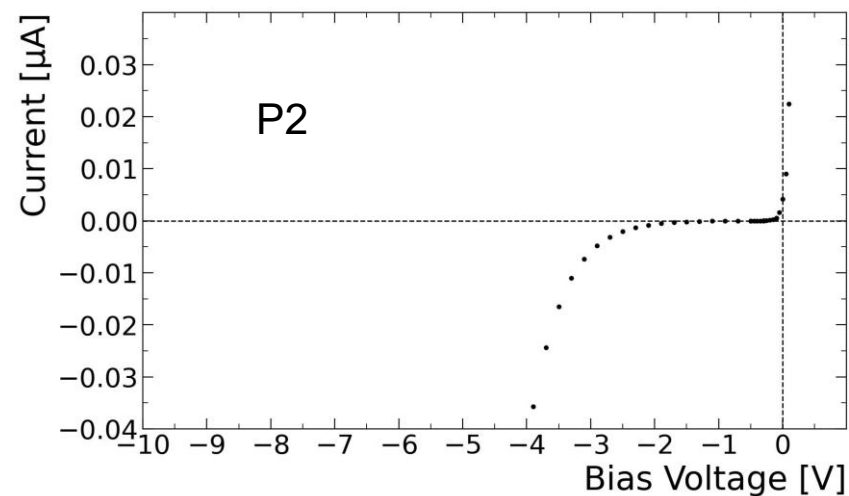
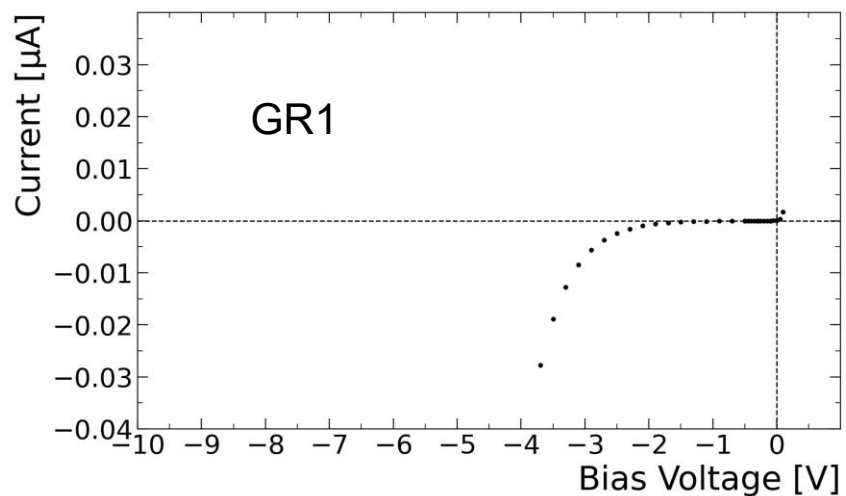
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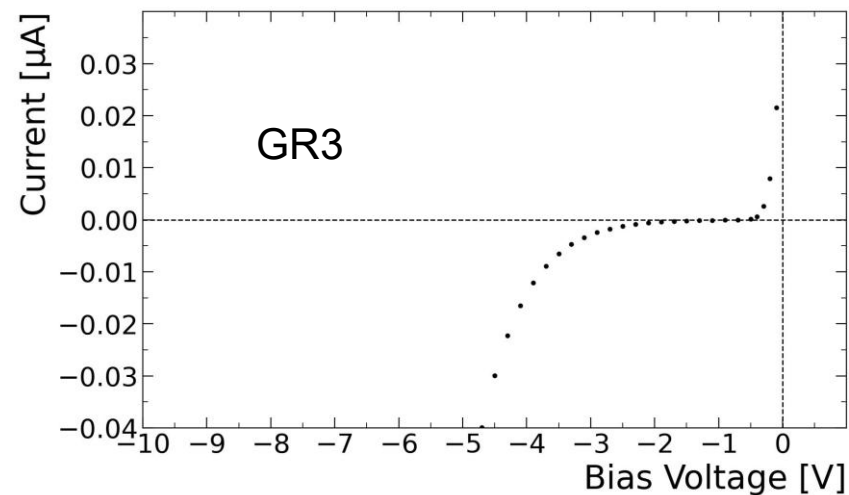
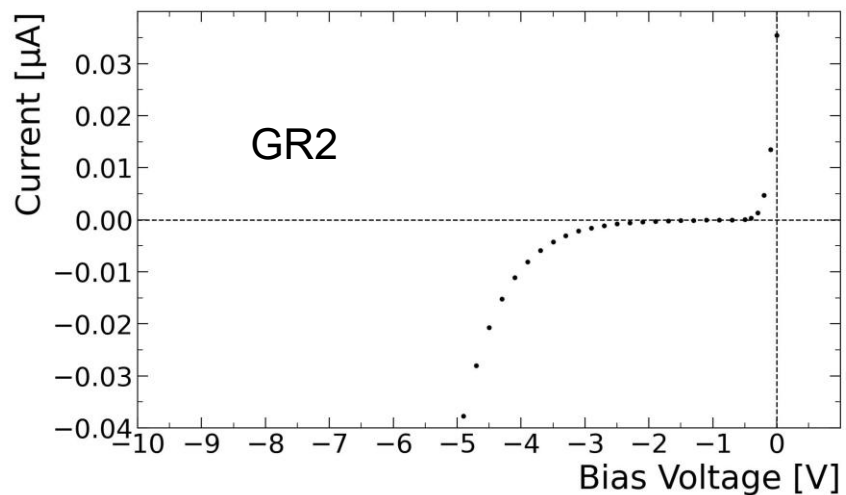
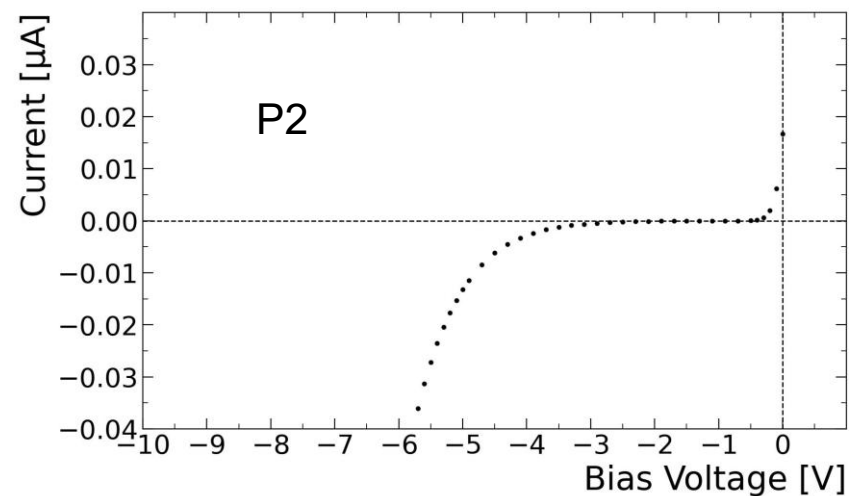
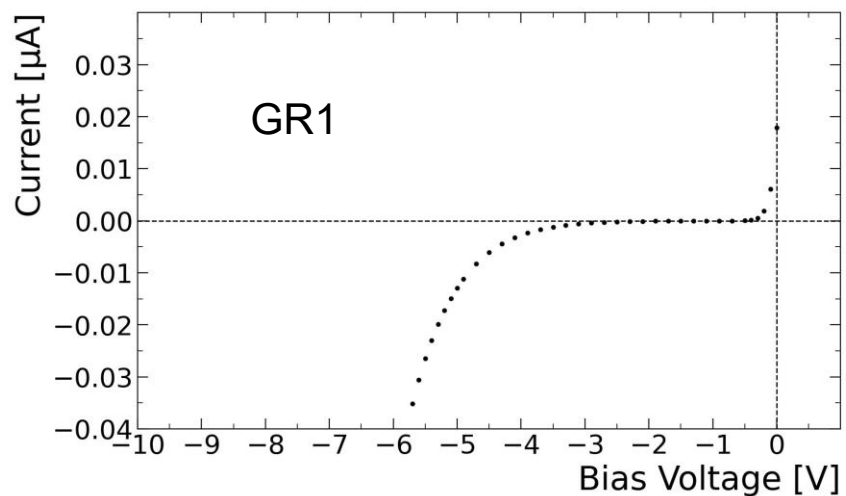
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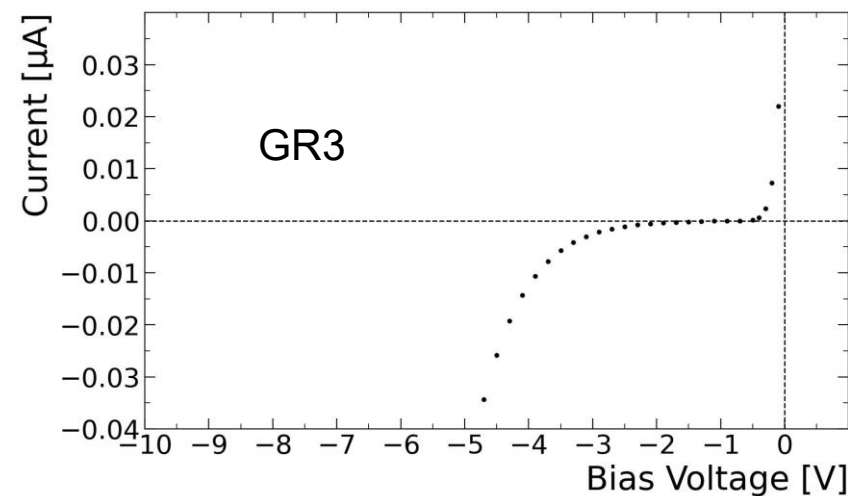
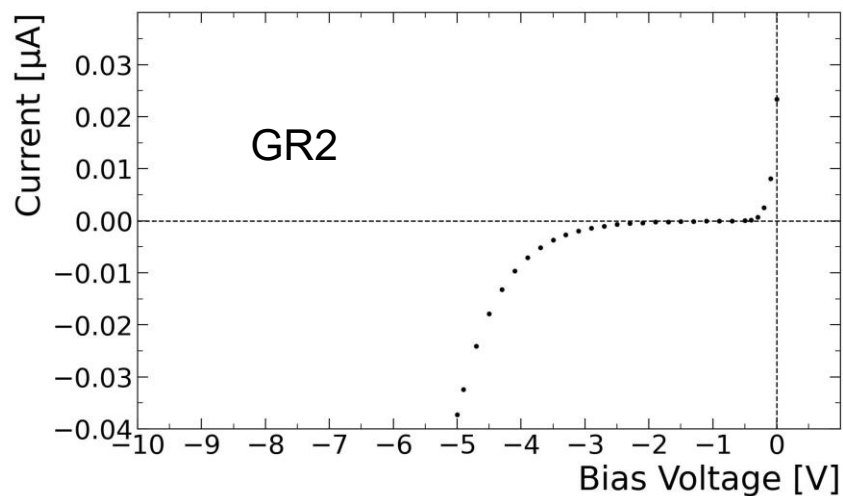
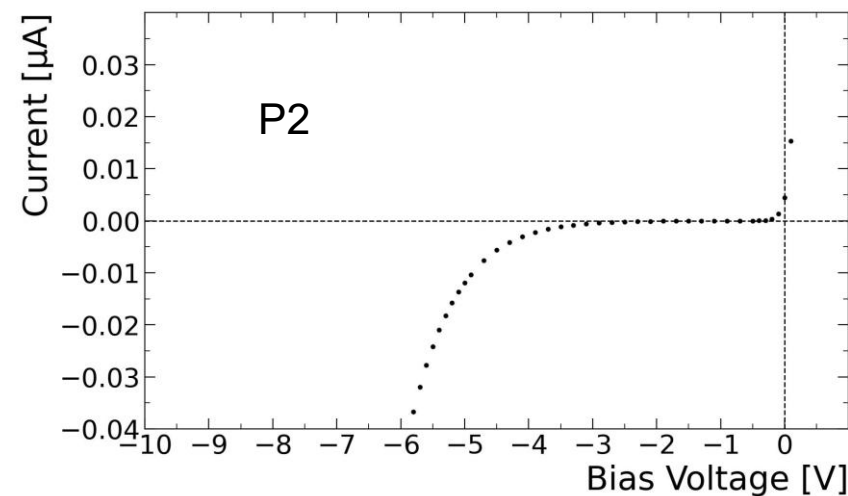
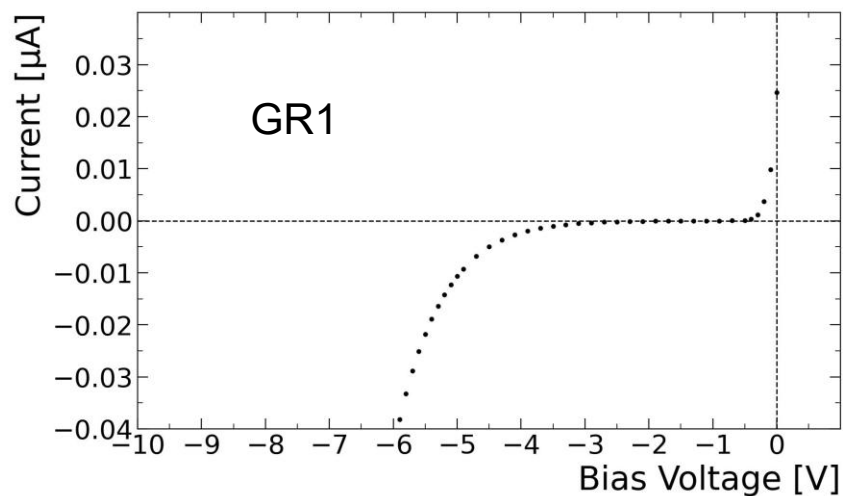
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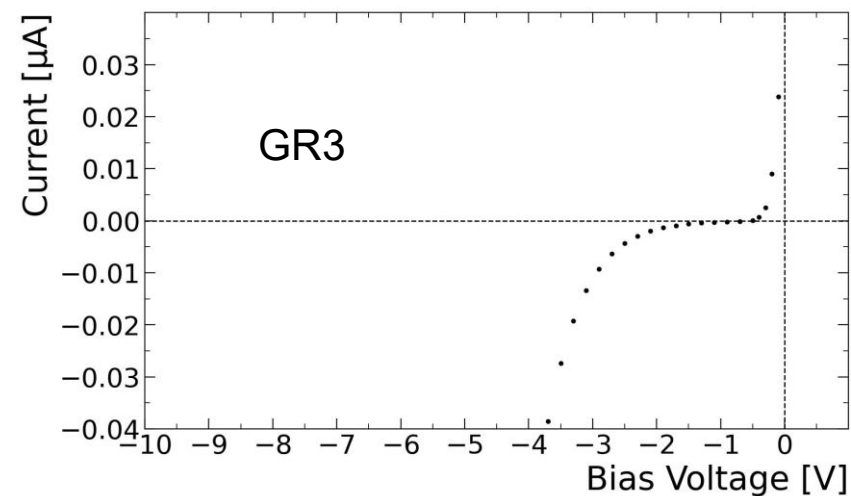
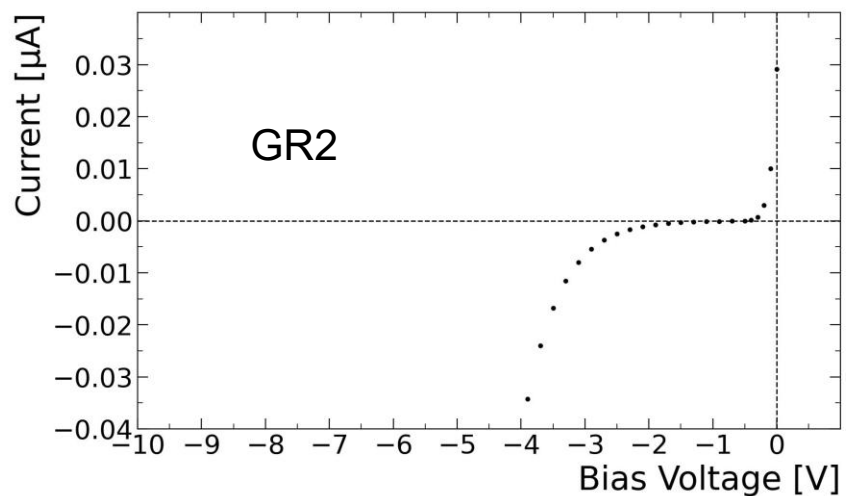
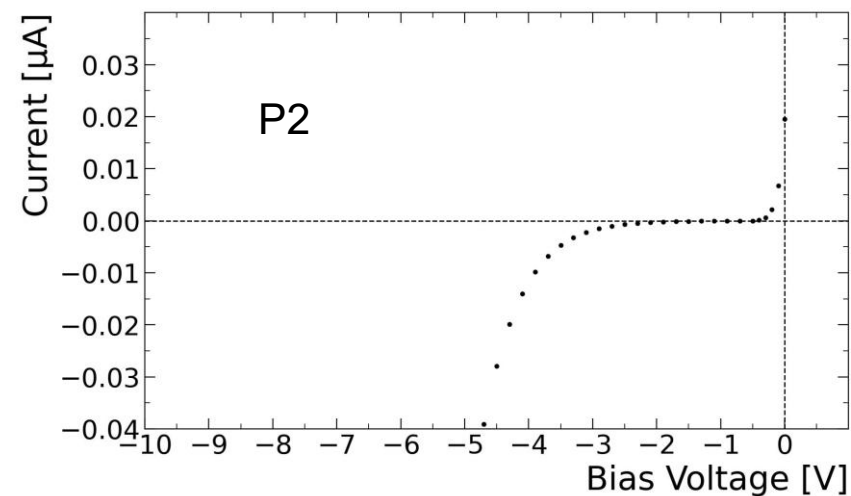
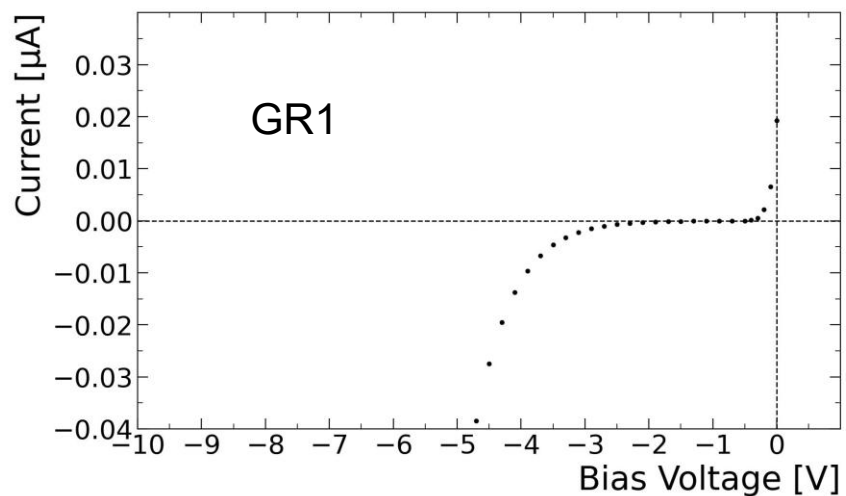
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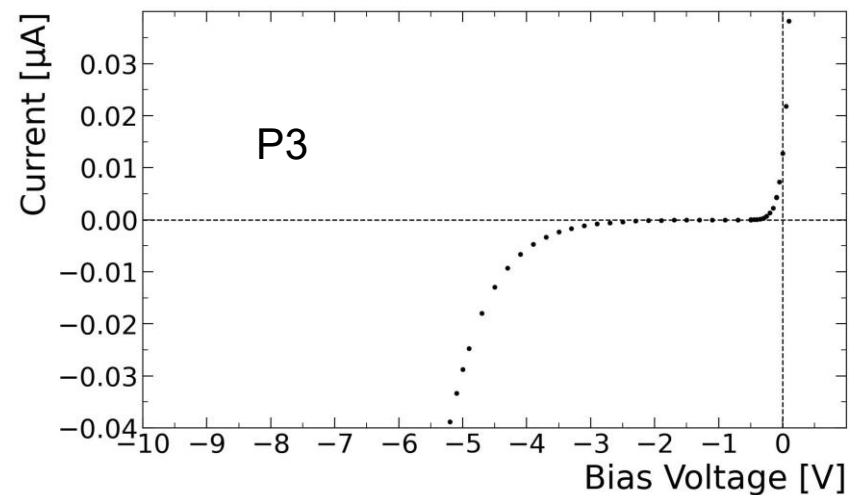
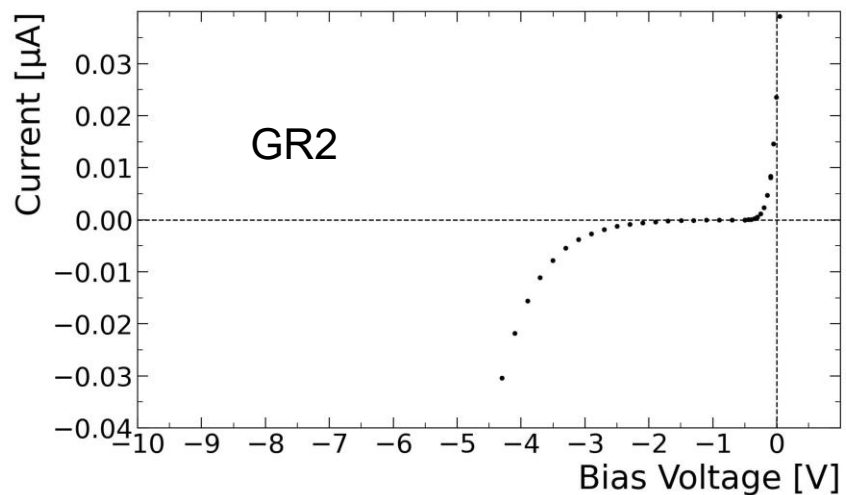
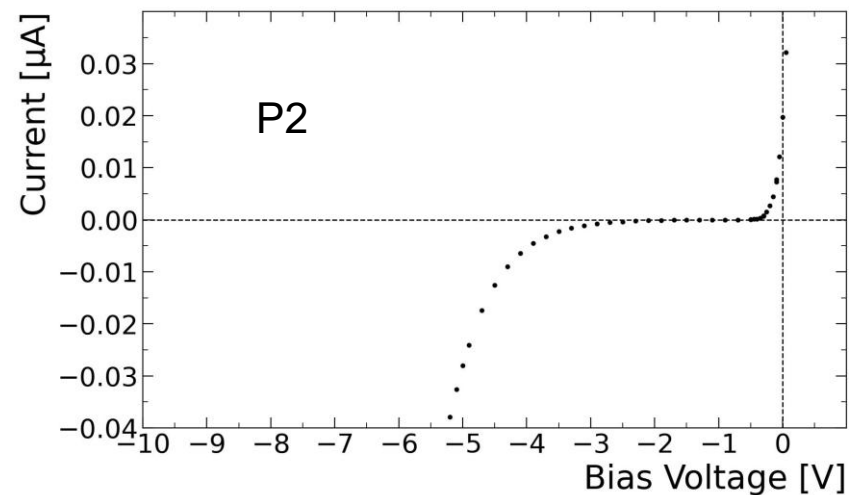
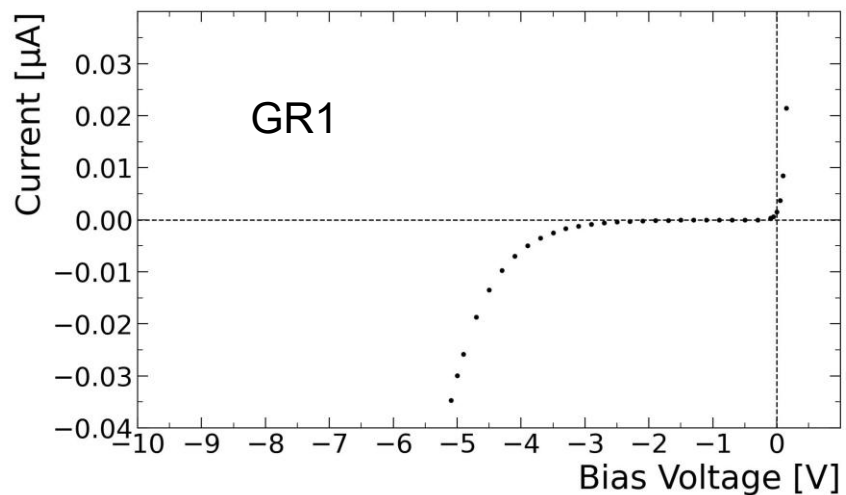
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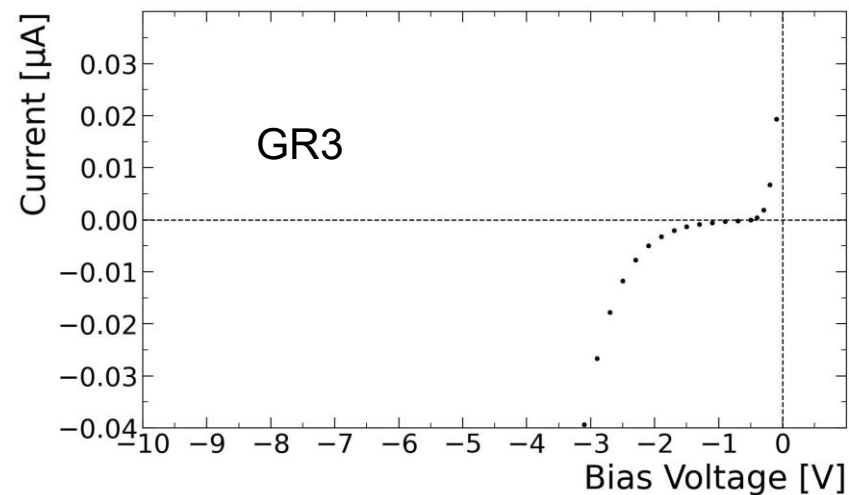
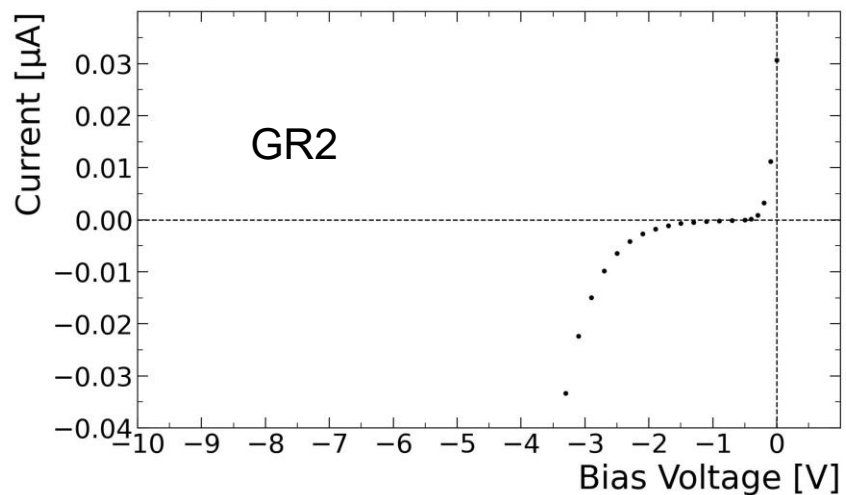
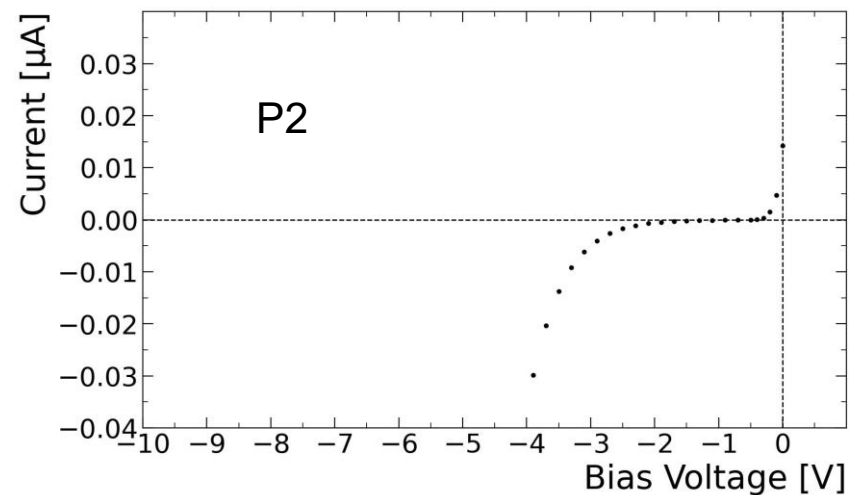
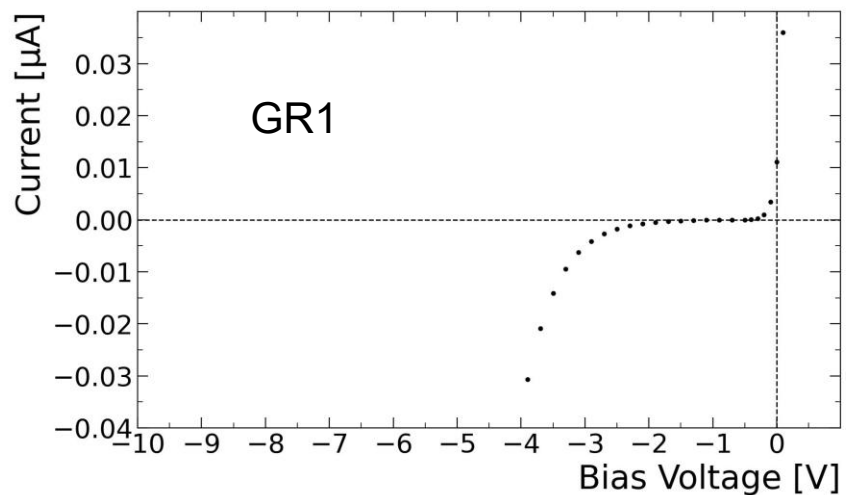
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□ CH1012A101G



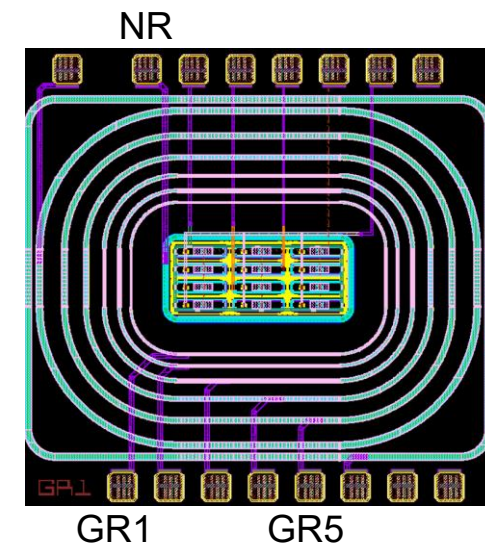
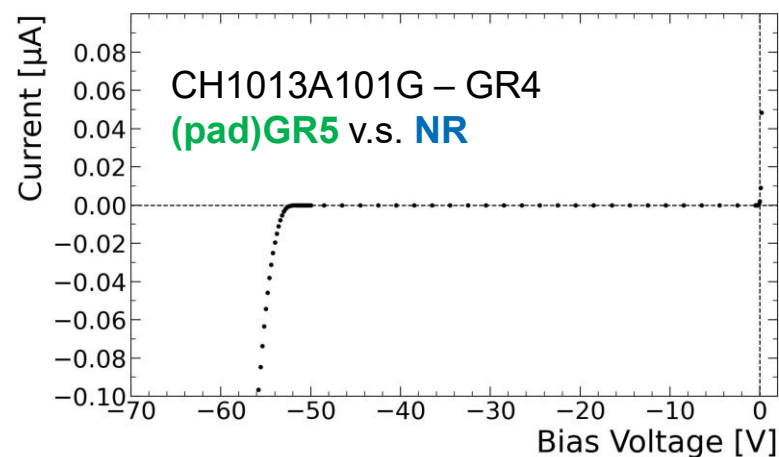
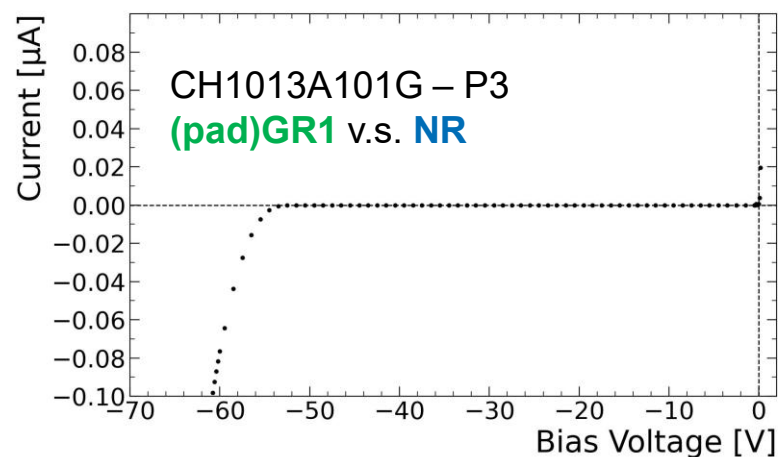
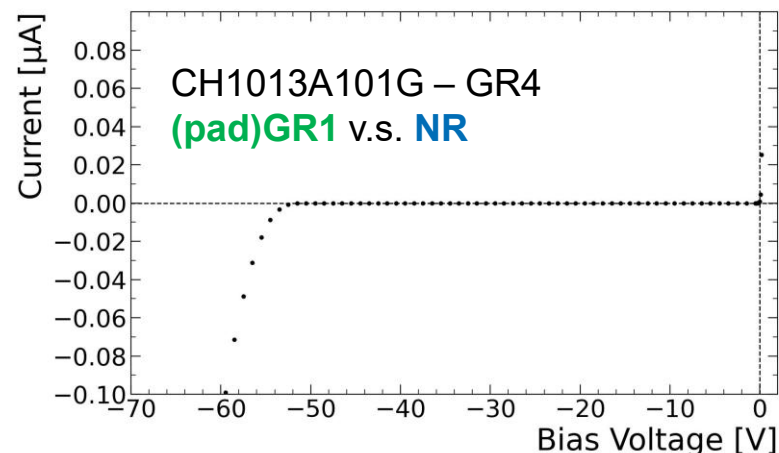
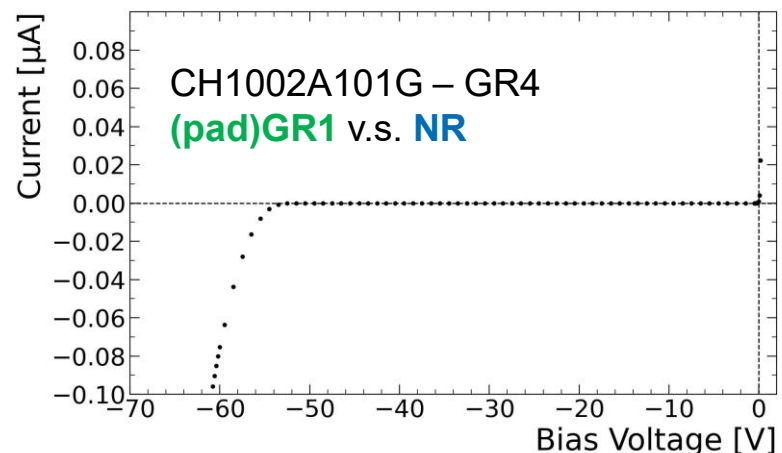
□ CH1013A101G



❑ 实际 IV 击穿电压远低于期望的 200 V，故检查其他 pad 之间的 IV 特性是否符合设计预期。

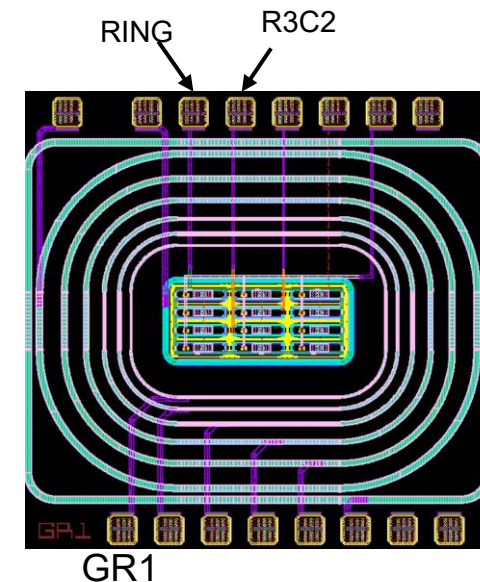
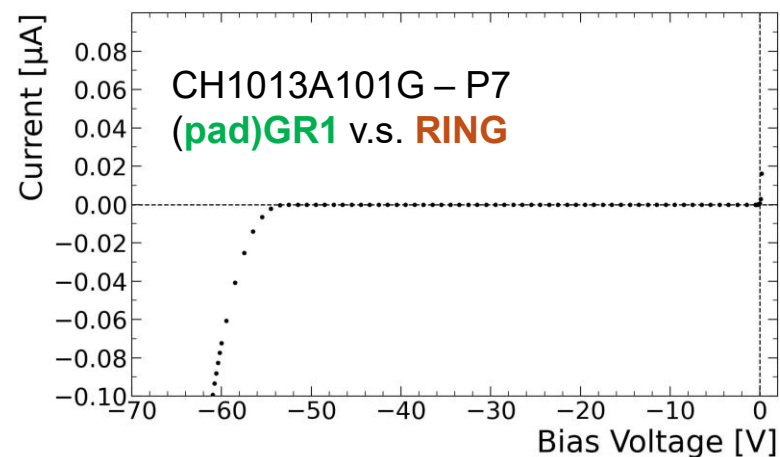
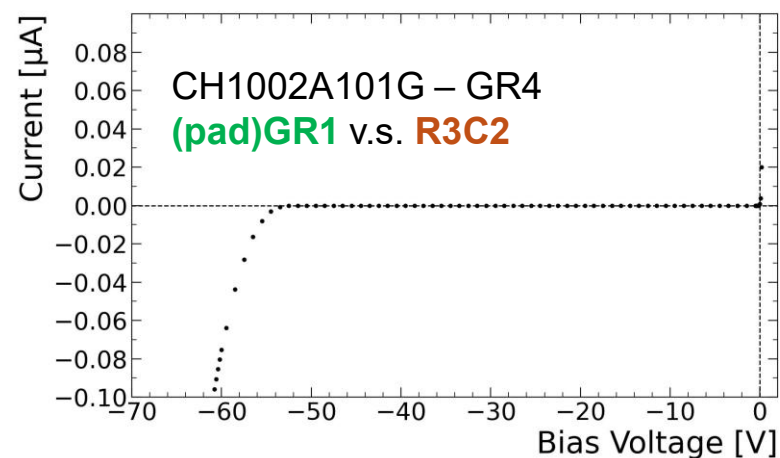
❑ 同一子阵列内：

- **guard-ring v.s. NR**，GR 负高压，NR 接地，预期为二极管特性



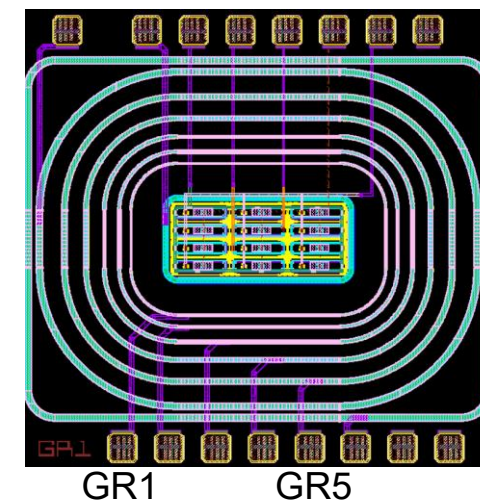
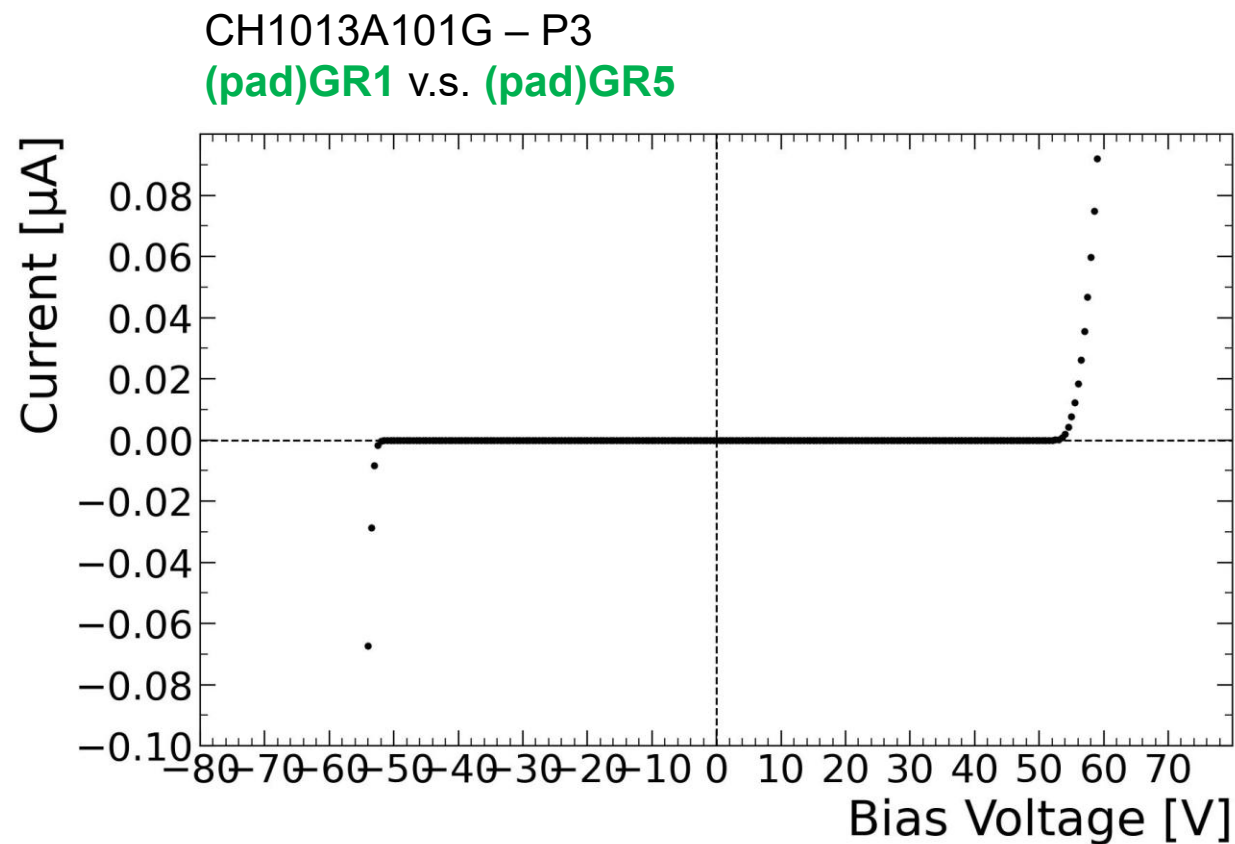
□ 同一子阵列内:

- **guard-ring v.s. pixel**, GR 负高压, pixel 接地, 预期为二极管特性



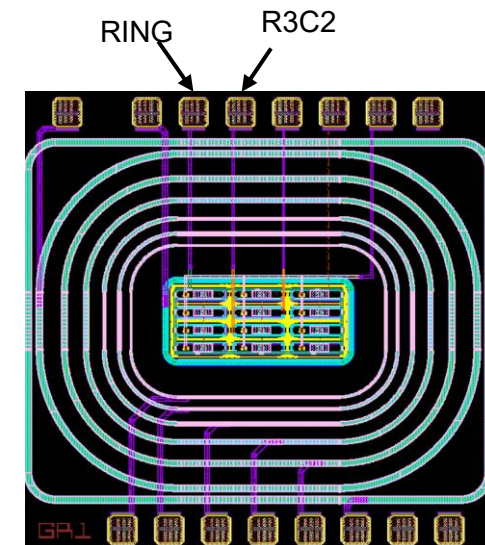
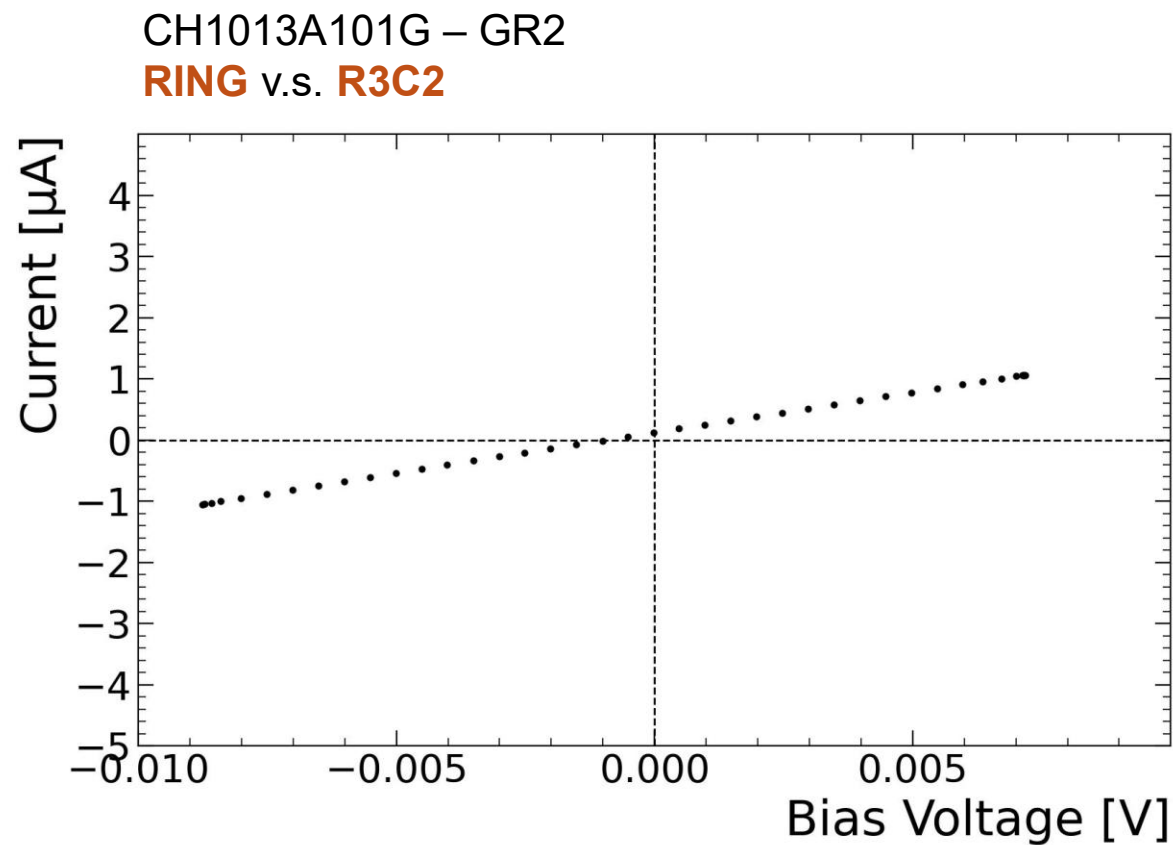
□ 同一子阵列内:

- guard-ring v.s. guard-ring, 预期为电阻特性



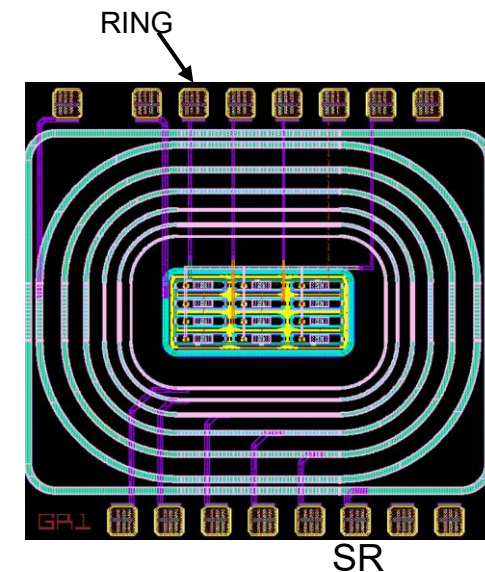
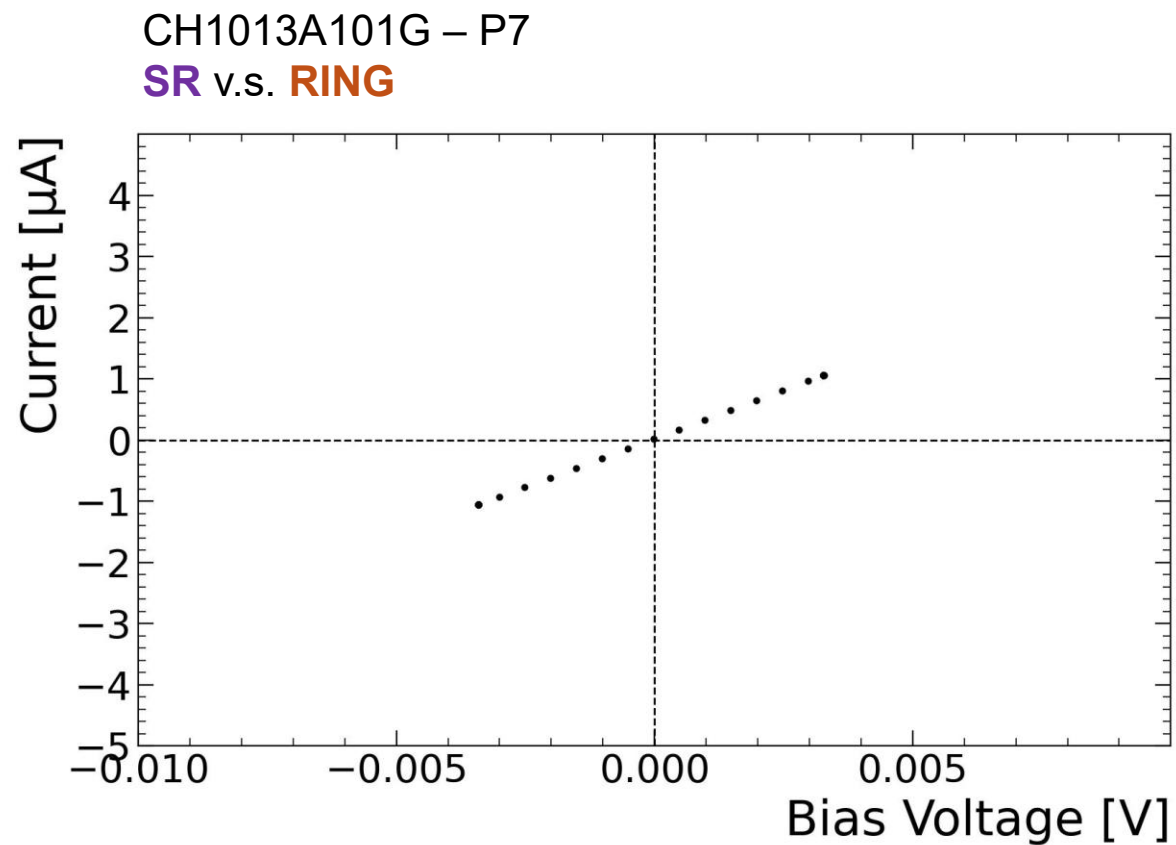
□ 同一子阵列内:

- pixel v.s. pixel, 预期为三极管特性



□ 同一子阵列内:

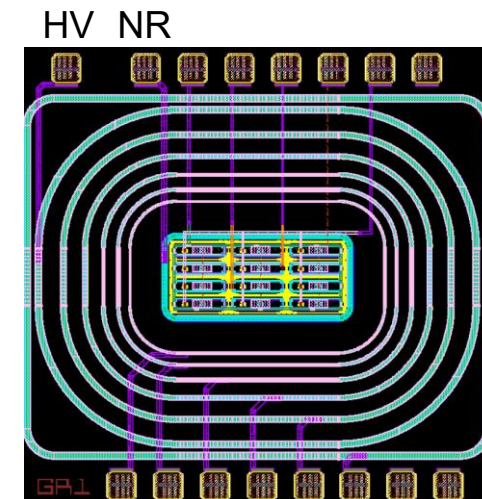
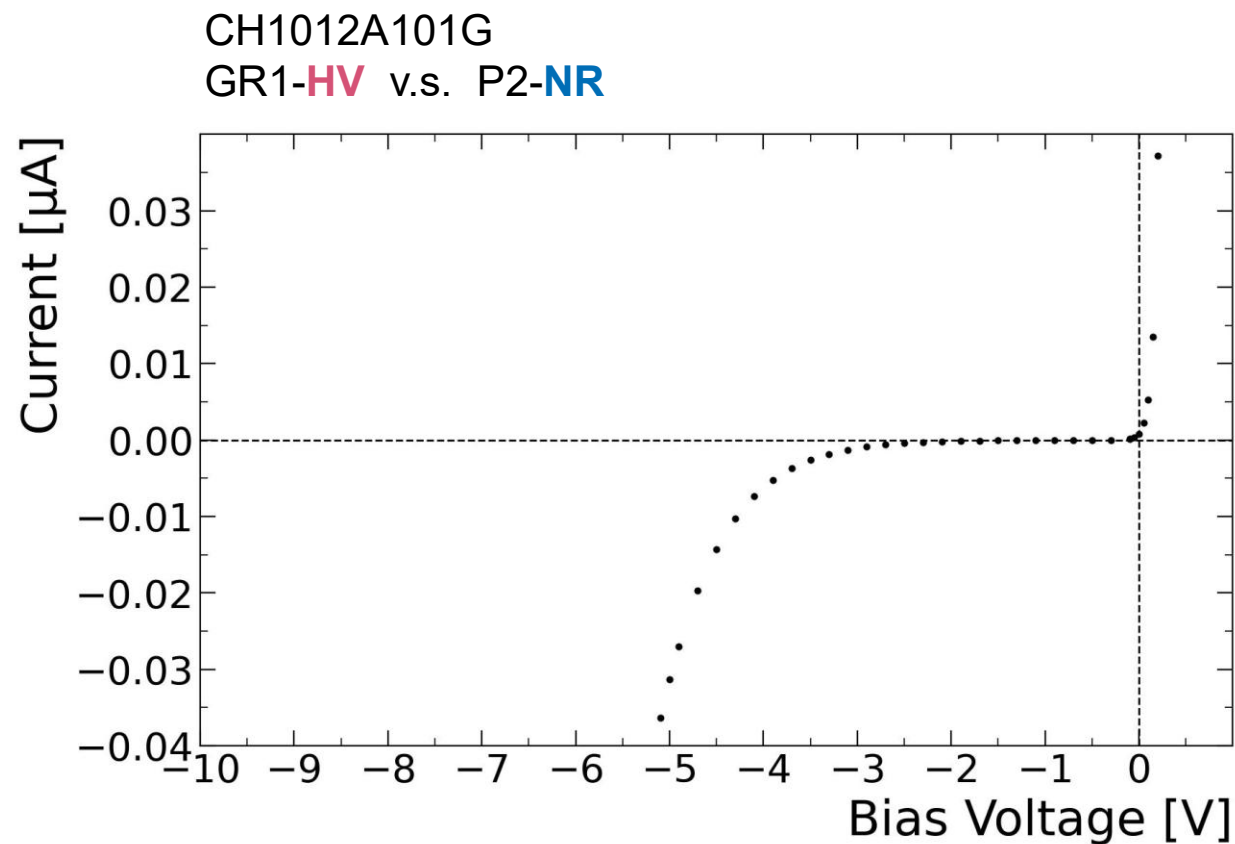
- **SR v.s. pixel**, 预期为二极管特性



□ 不同子阵列之间:

- **HV v.s. NR**, HV 负高压, NR接地, 预期为类似二极管 IV 特性

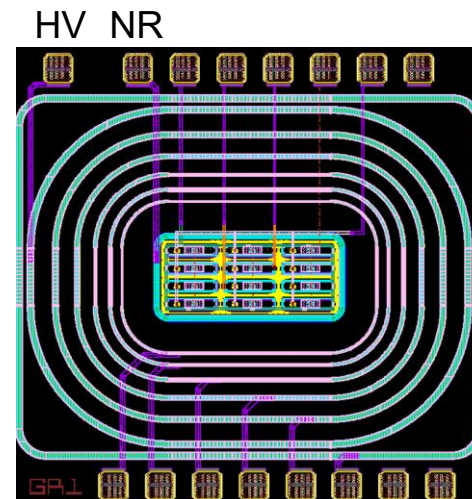
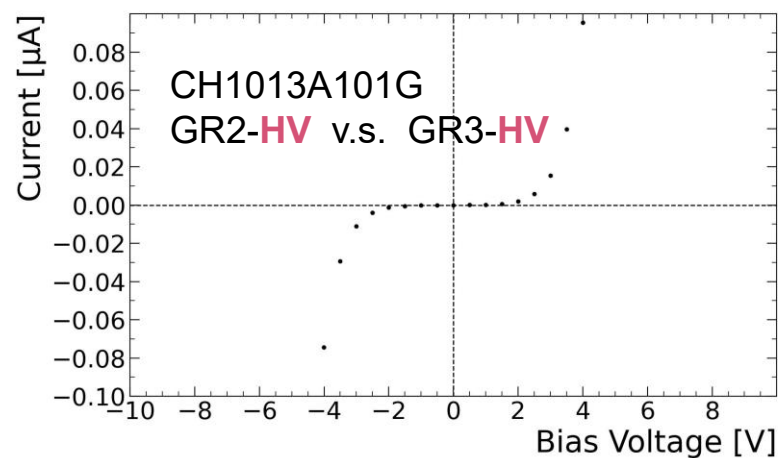
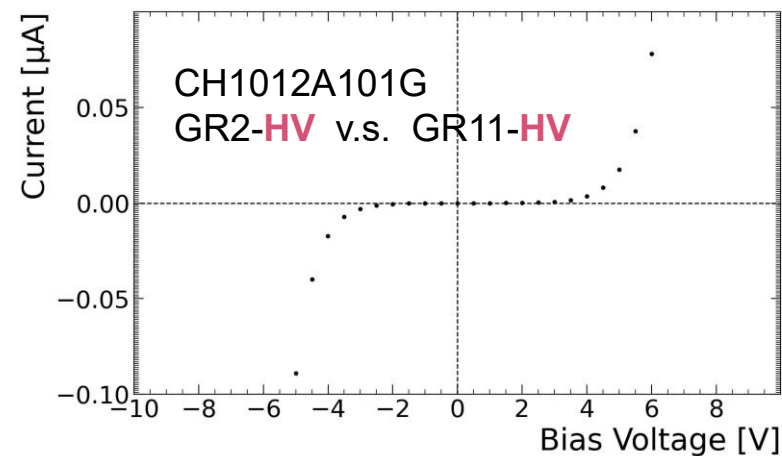
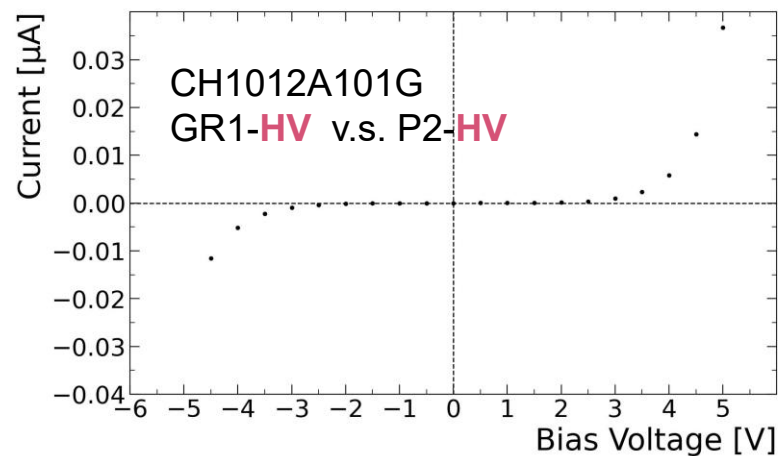
GR1	P2	P3	P4	P5	P6	P7	P8	P9	P10
GR2	GR3	GR4	GR5	GR6	GR7	GR8	GR9	GR10	GR11



不同子阵列之间:

- HV v.s. HV**, 预期为电阻特性

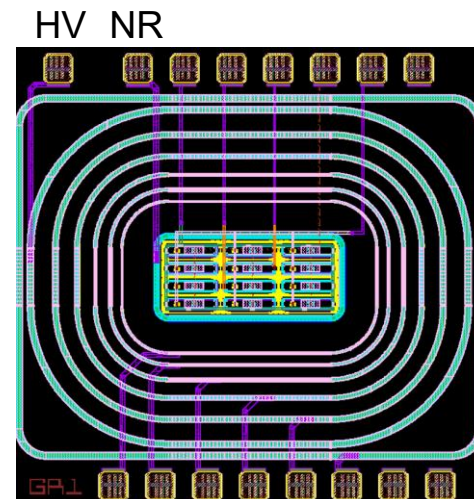
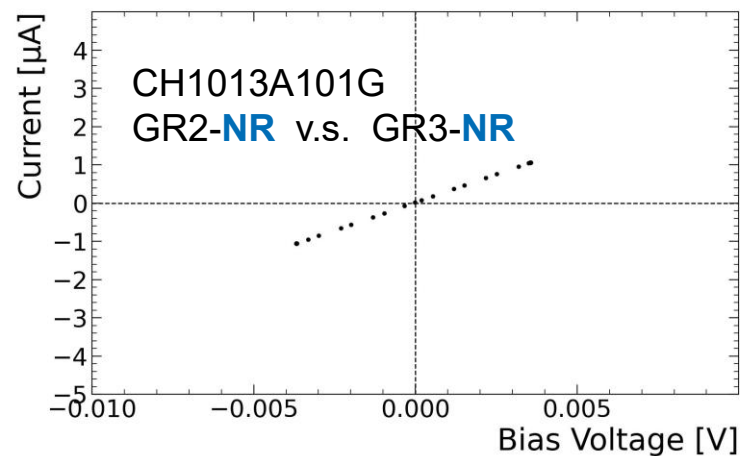
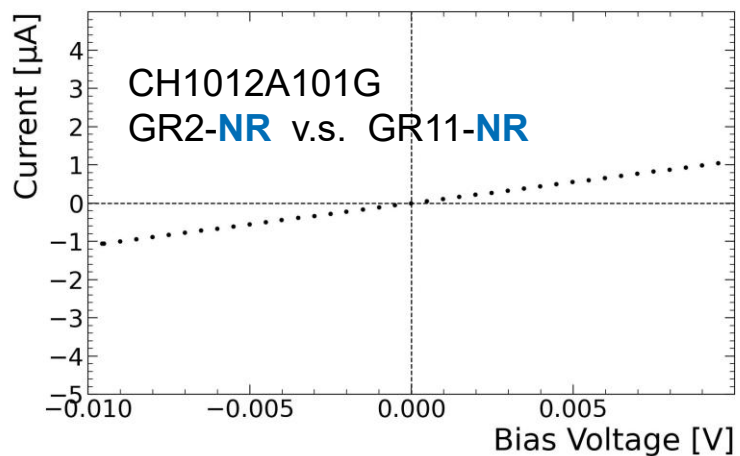
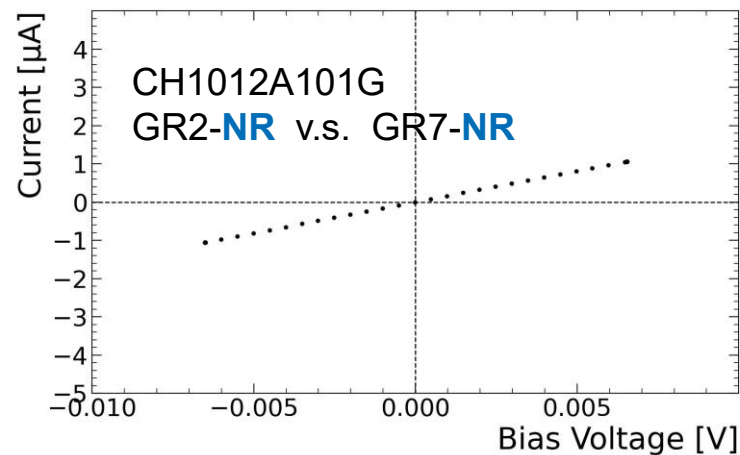
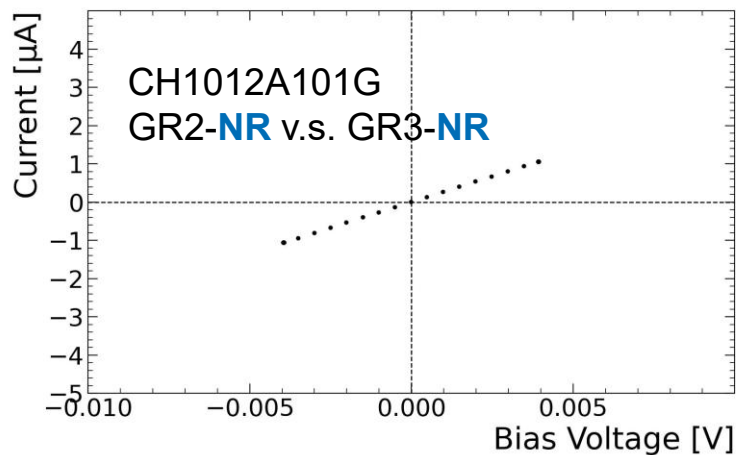
GR1	P2	P3	P4	P5	P6	P7	P8	P9	P10
GR2	GR3	GR4	GR5	GR6	GR7	GR8	GR9	GR10	GR11



不同子阵列之间:

- NR v.s. NR, 预期为三极管特性

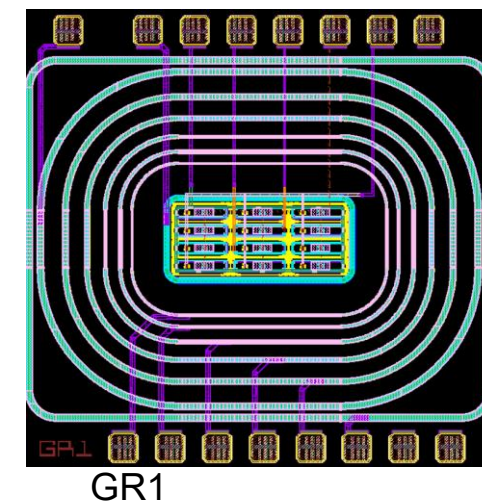
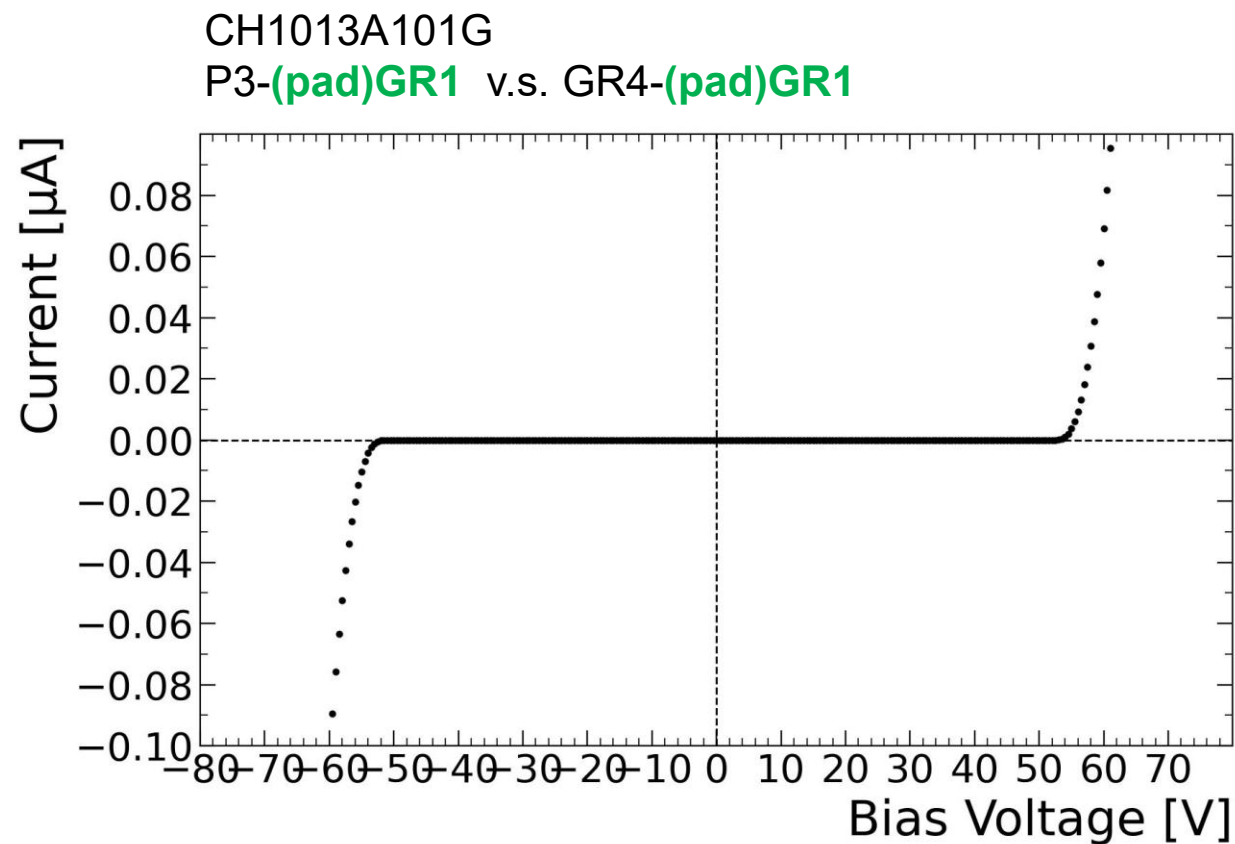
GR1	P2	P3	P4	P5	P6	P7	P8	P9	P10
GR2	GR3	GR4	GR5	GR6	GR7	GR8	GR9	GR10	GR11



□ 不同子阵列之间:

- **guard-ring v.s. guard-ring**, 预期为电阻特性

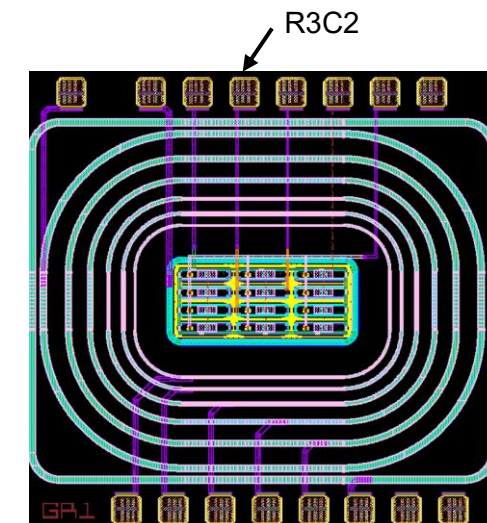
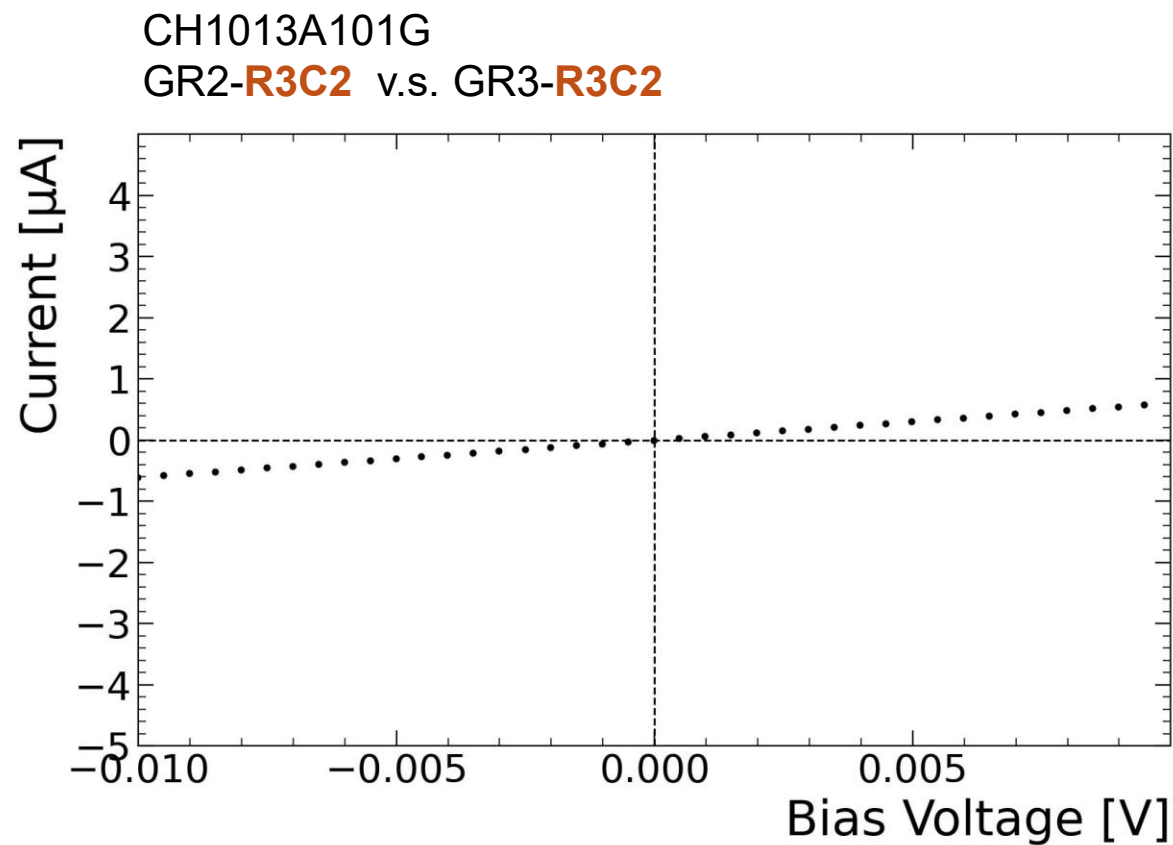
GR1	P2	P3	P4	P5	P6	P7	P8	P9	P10
GR2	GR3	GR4	GR5	GR6	GR7	GR8	GR9	GR10	GR11



□ 不同子阵列之间:

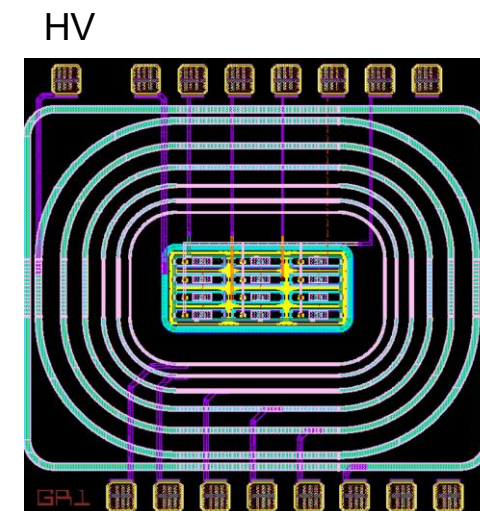
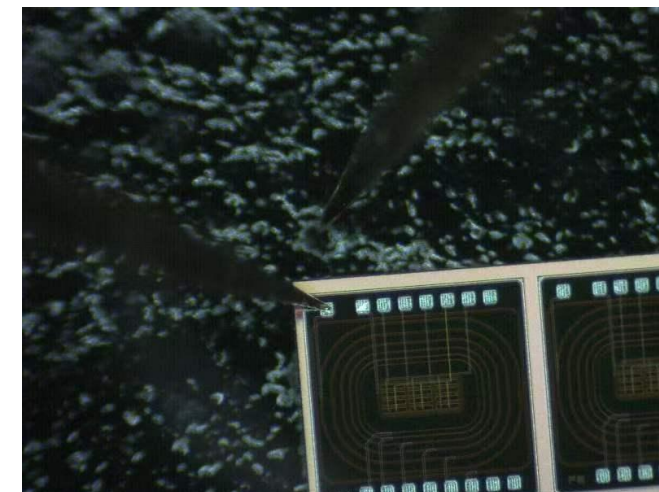
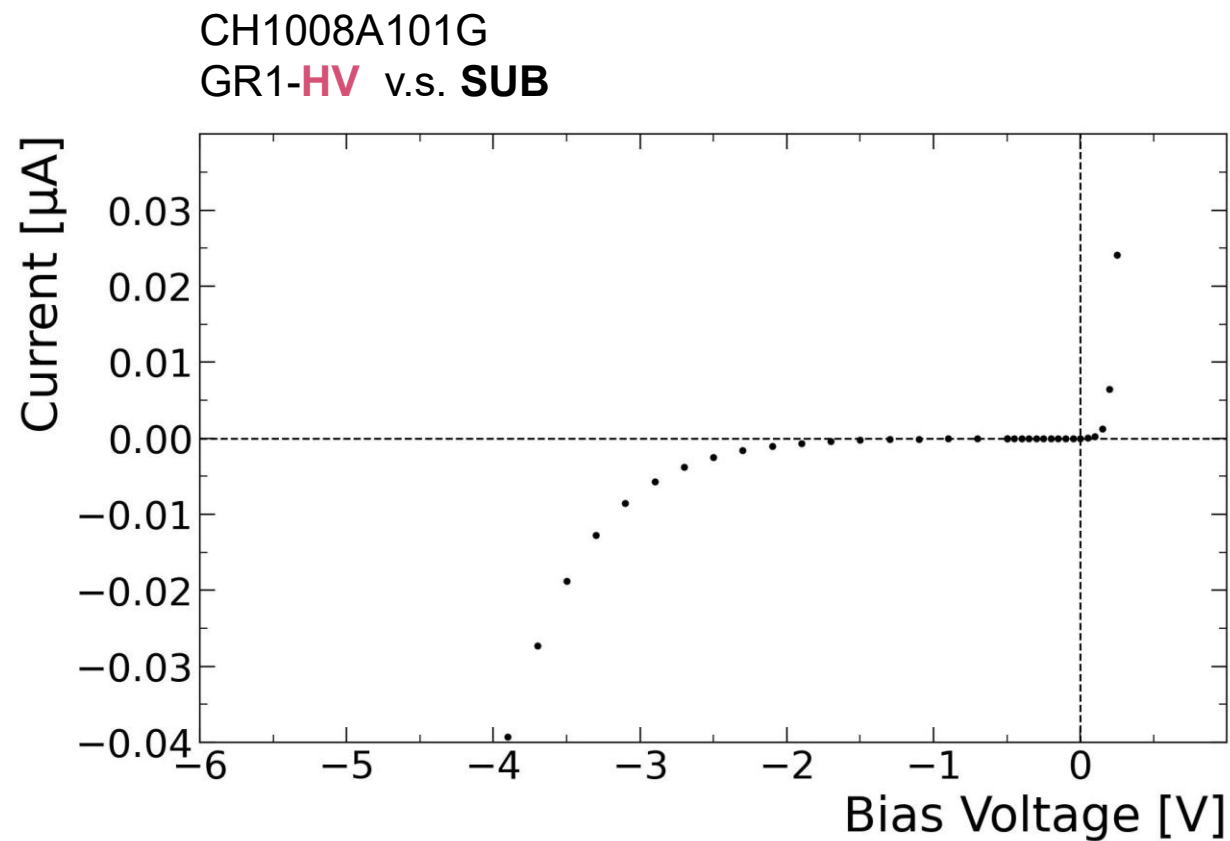
- pixel v.s. pixel, 预期为三极管特性

GR1	P2	P3	P4	P5	P6	P7	P8	P9	P10
GR2	GR3	GR4	GR5	GR6	GR7	GR8	GR9	GR10	GR11

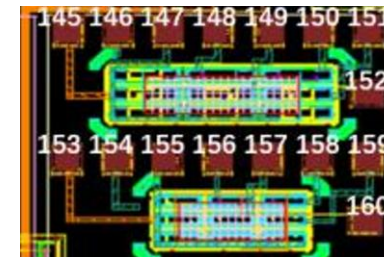


□ 不同子阵列之间:

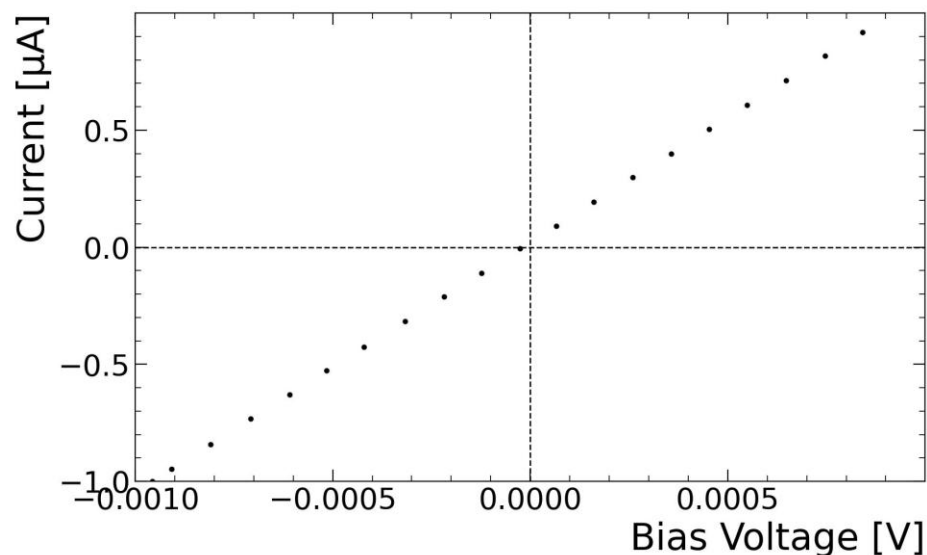
- **HV v.s. SUB**, HV 负高压, SUB 由碳导电胶引出



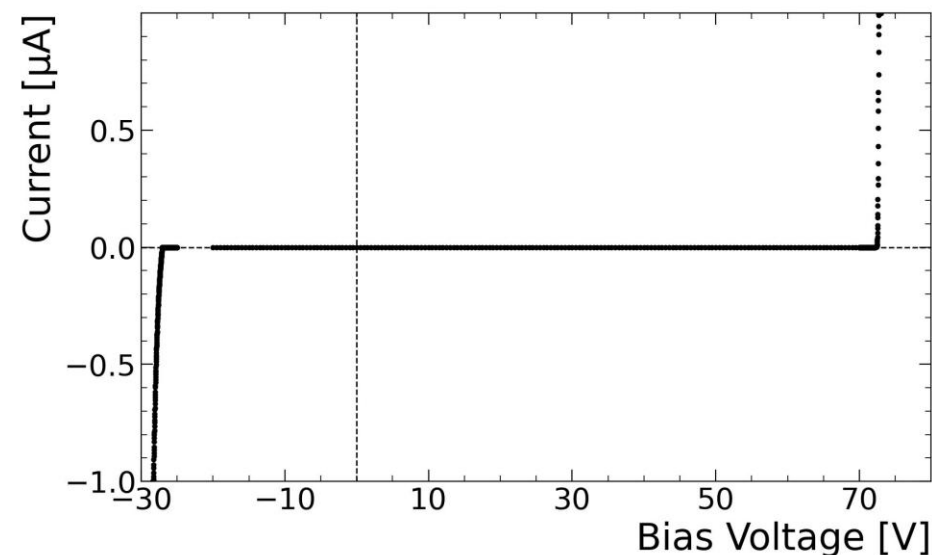
- 用已知符合预期的 COFFEE3 验证正常的 HV-HV 和 n-well 之间的 IV 特性



pad 145 v.s. 153 (pixel & pixel)

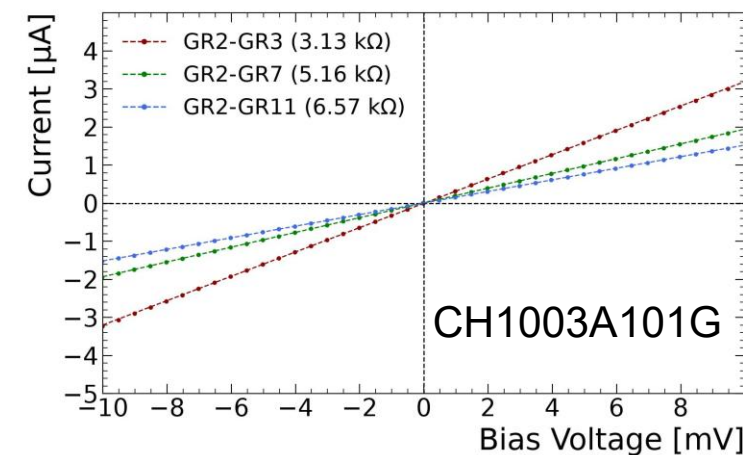
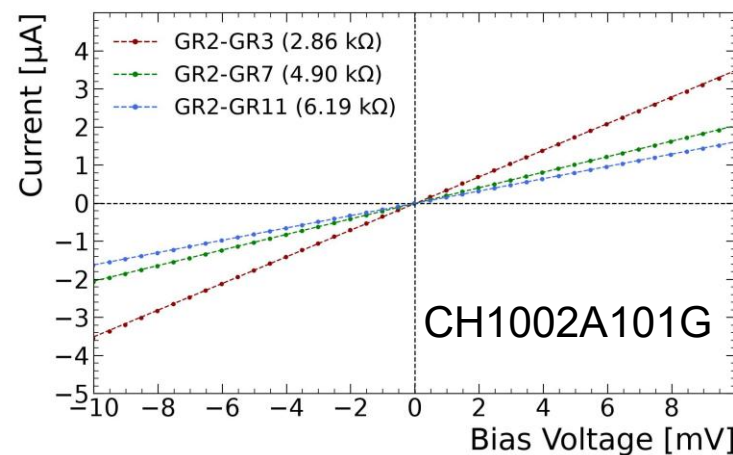
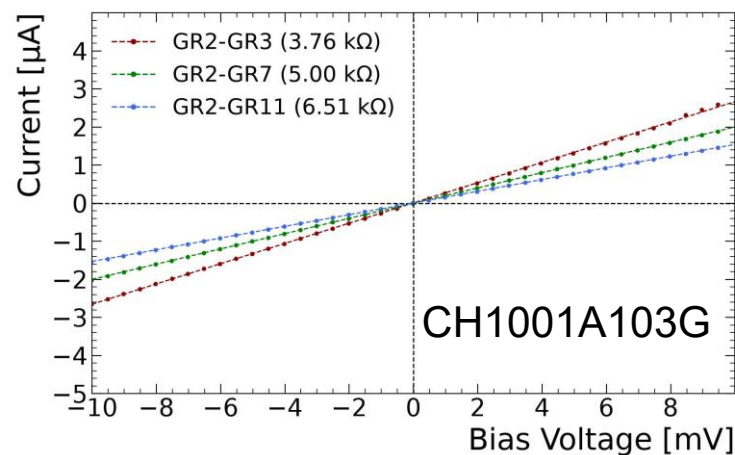


pad 148 v.s. 151 (HV & HV)



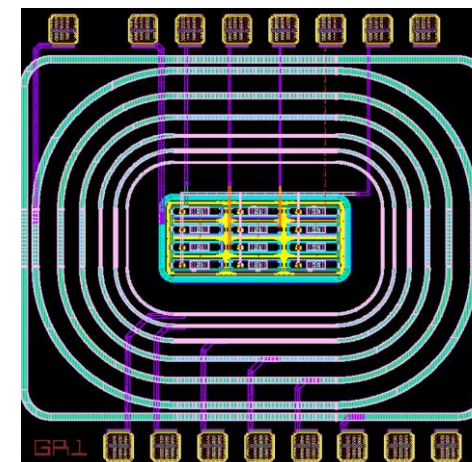
- HV – HV 和 n-well – n-well 两种 IV 特性与 ChiR1.0 的情况刚好相反

- 不同子阵列之间的 NR-pad 的 IV 测试，期望不同子阵列的 NR 之间绝缘或三极管特性。
- 对总共 13 种晶圆的 A 阵列芯片 GR2-GR3, GR2-GR7, GR2-GR11 之间的 NR 进行 IV 扫描，以判断注入参数是否产生影响。

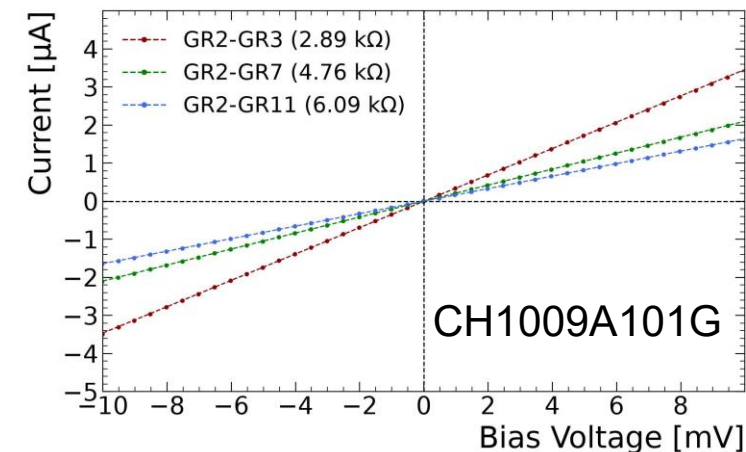
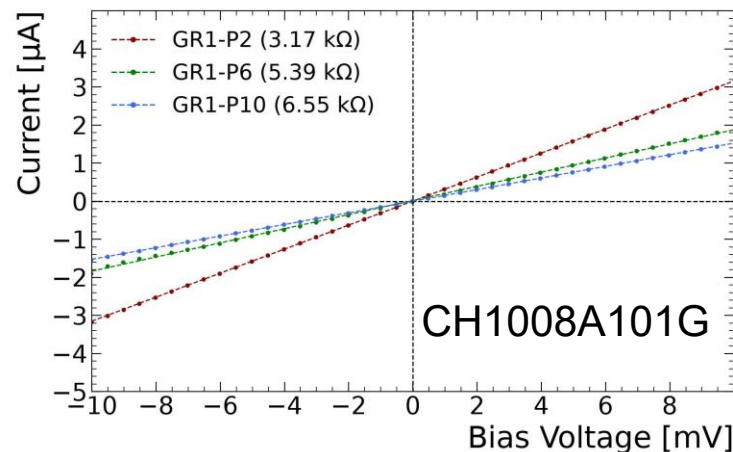
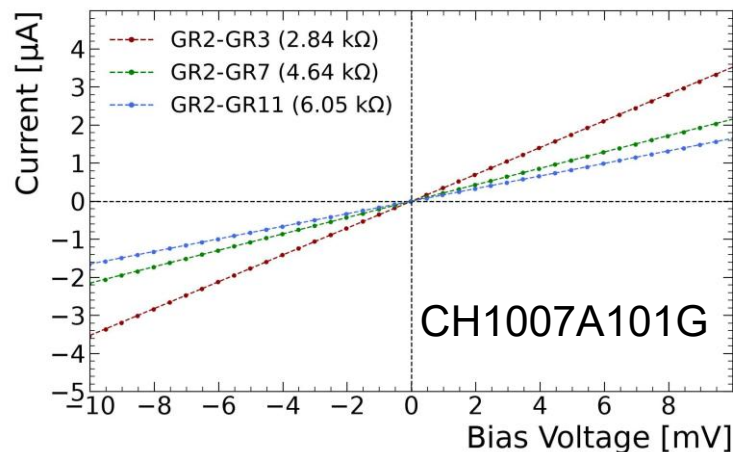
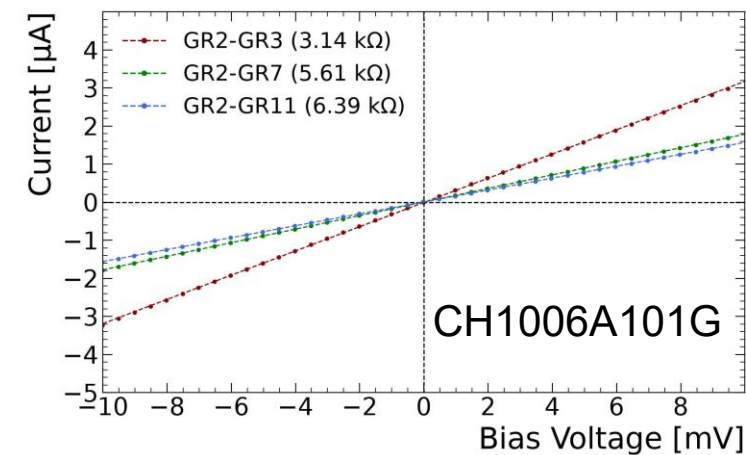
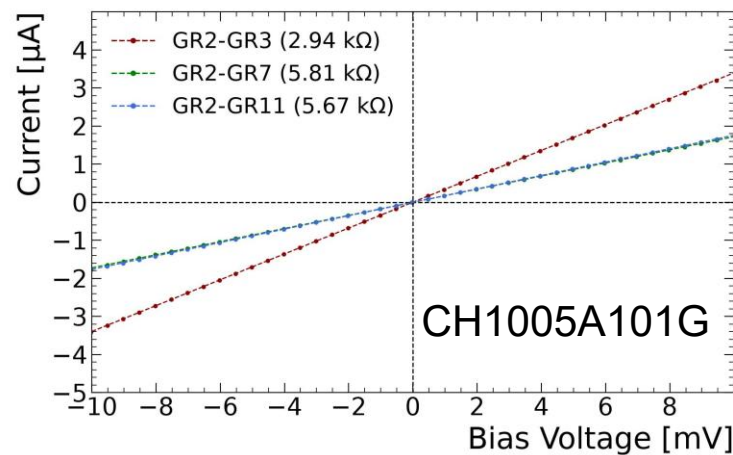
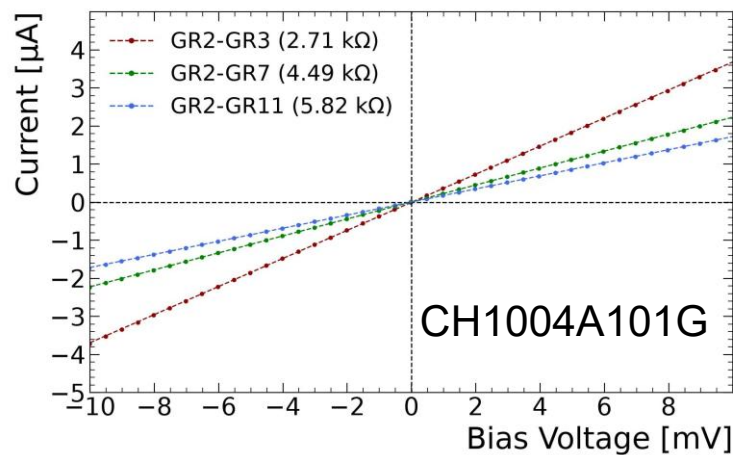


GR1	P2	P3	P4	P5	P6	P7	P8	P9	P10
GR2	GR3	GR4	GR5	GR6	GR7	GR8	GR9	GR10	GR11

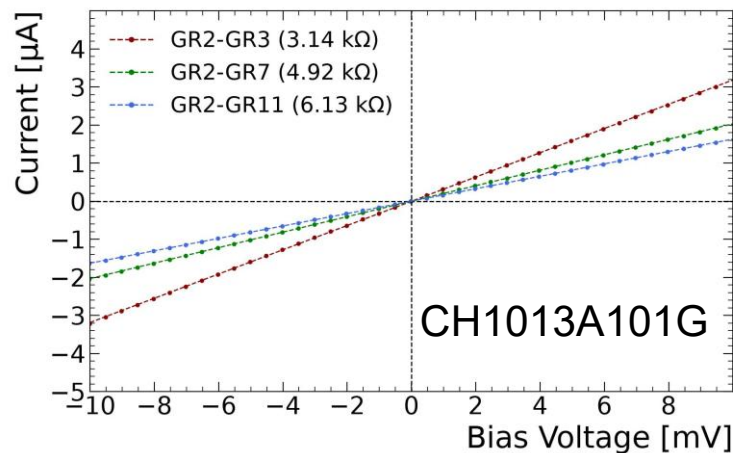
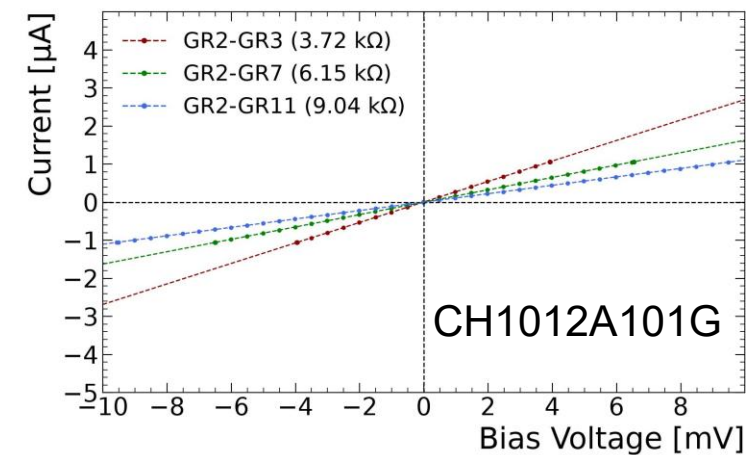
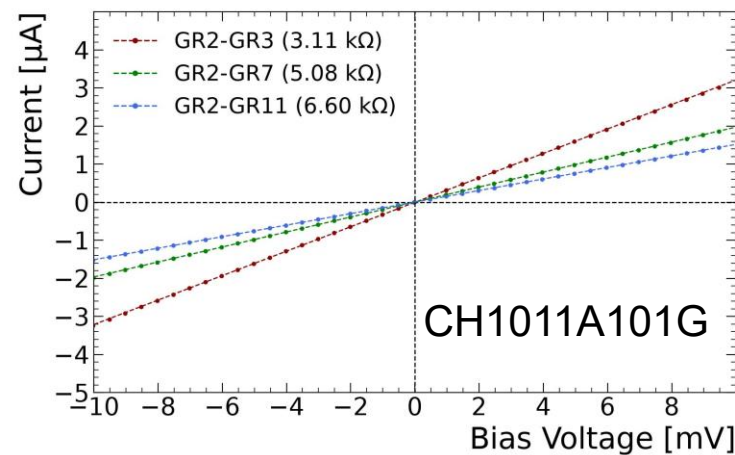
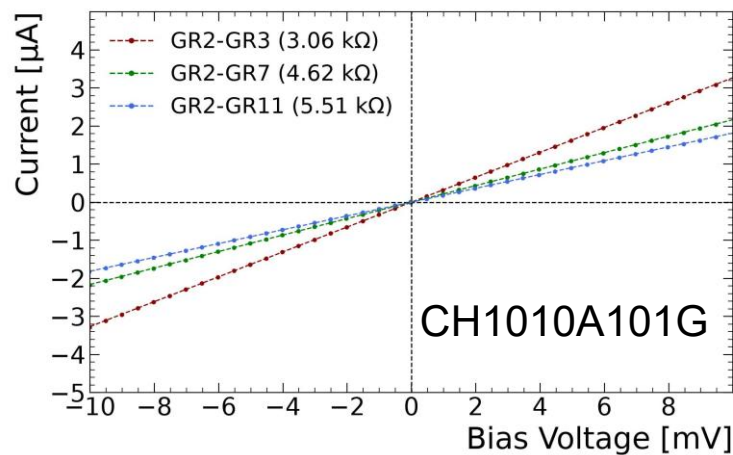
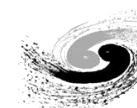
NR



ChiR1.0 A IV NR-NR 接通测试



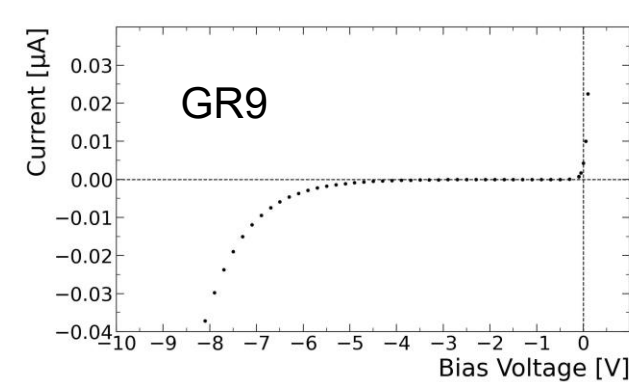
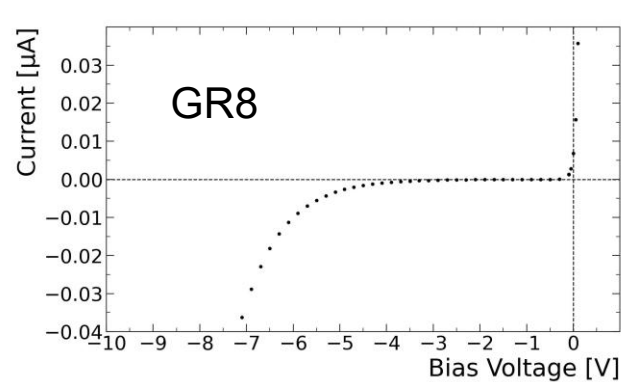
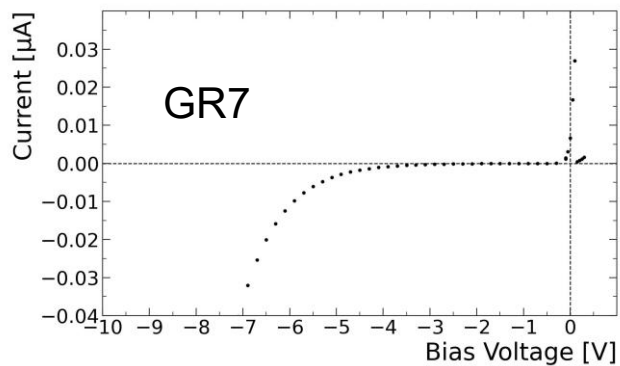
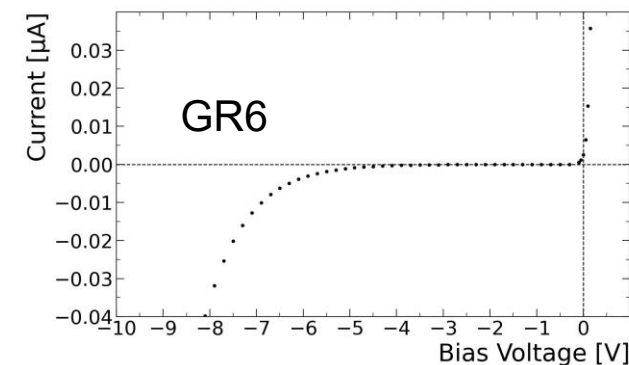
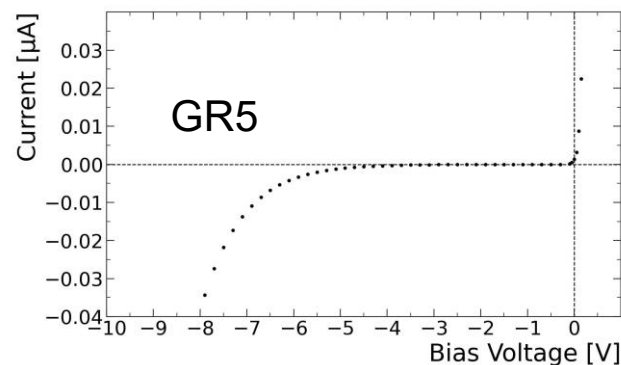
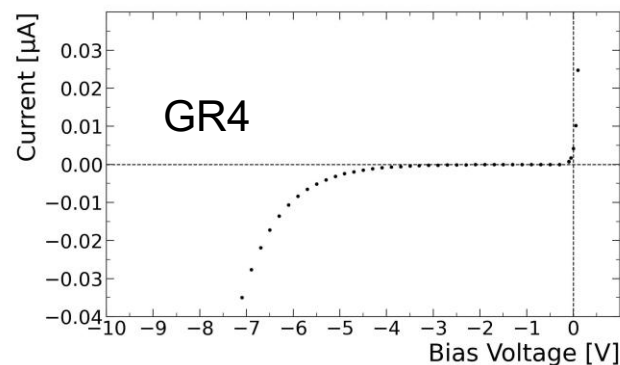
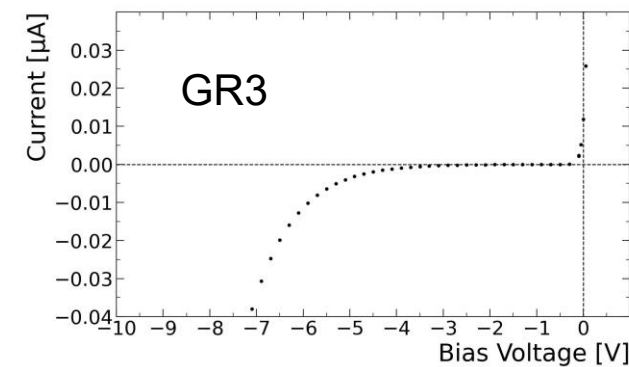
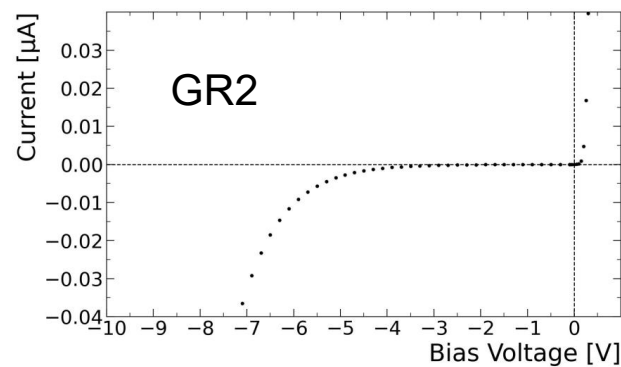
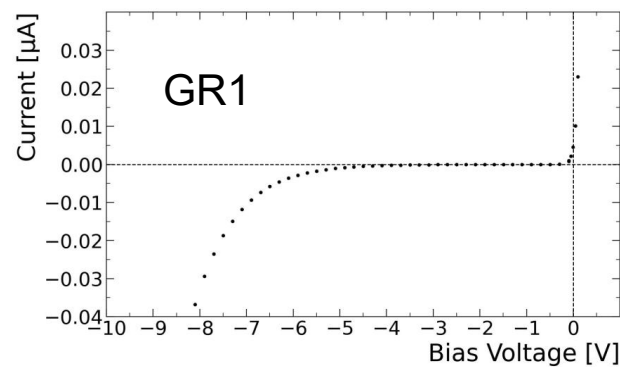
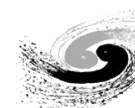
ChiR1.0 A IV NR-NR 接通测试



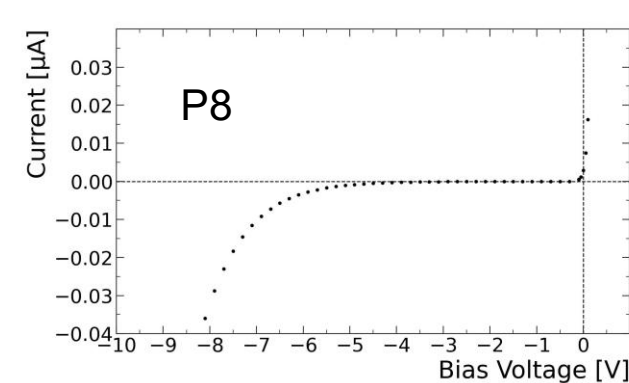
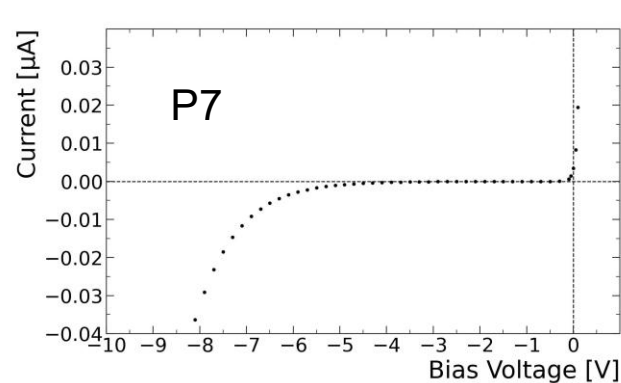
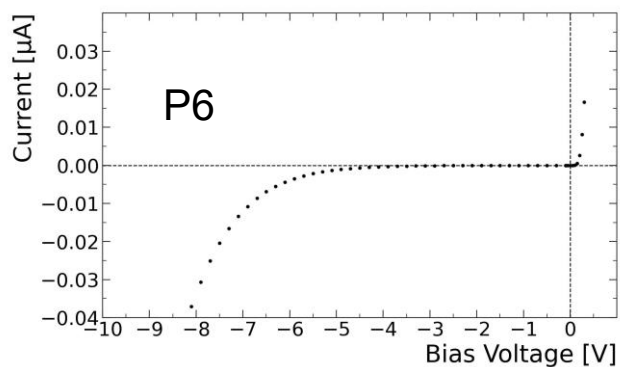
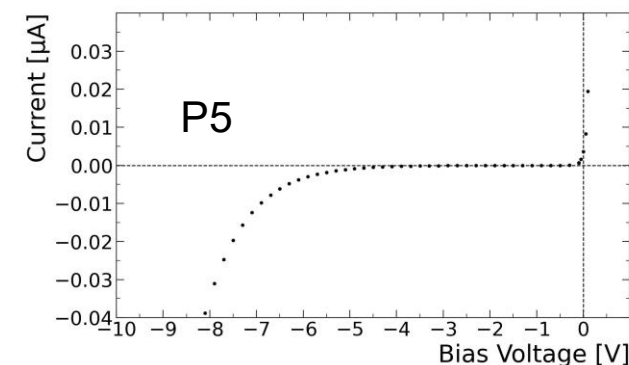
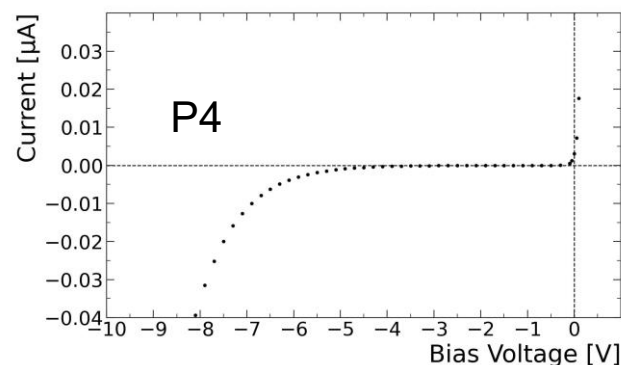
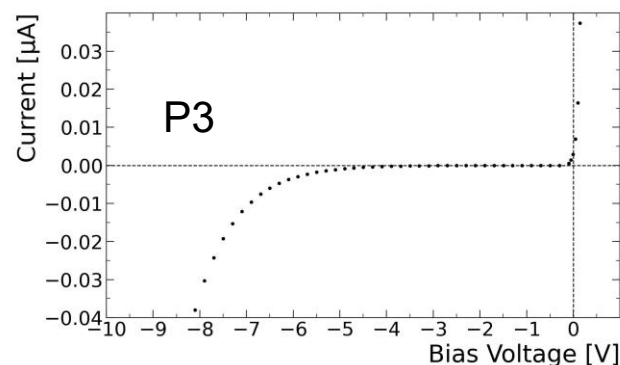
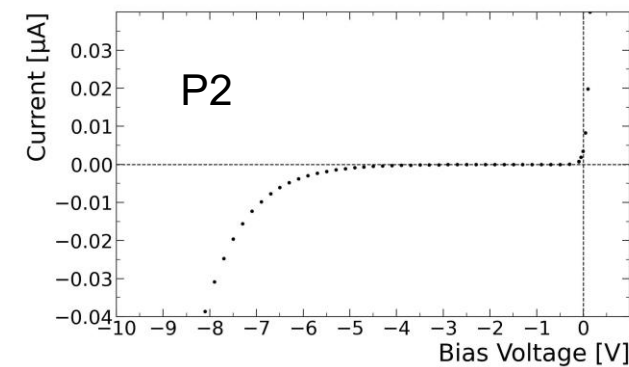
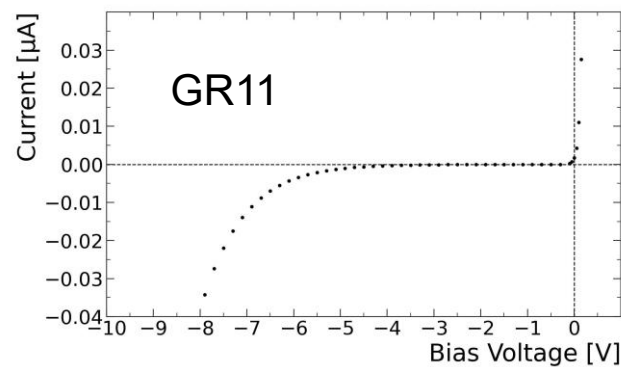
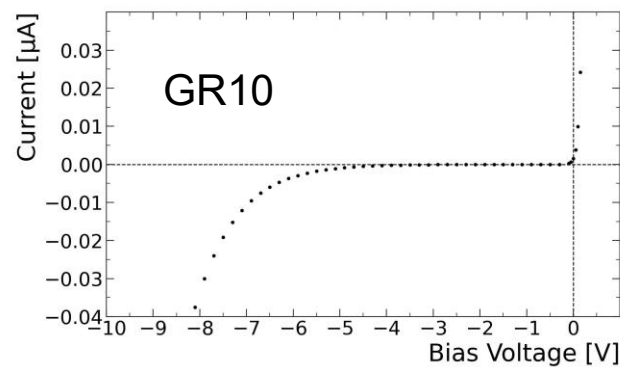
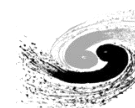
- IV 测试表明，**实际流片的击穿电压 ($\sim 5\text{ V}$ 限流 $1\text{ }\mu\text{A}$) 远低于设计指标 (200 V)**，原因待查明。
- 本次流片的不同晶圆注入参数对击穿电压的影响不大，但 #02 晶圆不包含 DPW，相比其他晶圆的击穿电压有所提升；#12 晶圆不包含 VDNW，但击穿电压受其影响不显著；
- 其他补充的 IV 扫描表明，
 - 每个子阵列的 NR、像素 N-well 之间为纯电阻接通，而 HV、guard-ring 之间不是纯电阻；
 - guard-ring 与 NR 的击穿电压 ($\sim 50\text{ V}$) 显著高于 HV 与 NR 的击穿电压 ($< 5\text{ V}$)
 - 推测：ChiR1.0 基底可能表现为低阻 n 型，而不是高阻 p 型

Thank you for your attention!

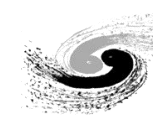
Backup: CH1002A101G 全部 20 个 IV 测试结果



Backup: CH1002A101G 全部 20 个 IV 测试结果



Backup: CH1002A101G 全部 20 个 IV 测试结果



中国科学院高能物理研究所
Institute of High Energy Physics, CAS

